

(MOS-FET) Metal Oxide Semiconductor Field- Effect Transistors

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Prodi S1-SK

2017

Bipolar Junction Transistor Structure

1. 3 Layers
2. Difficult to make, especially in sub micron

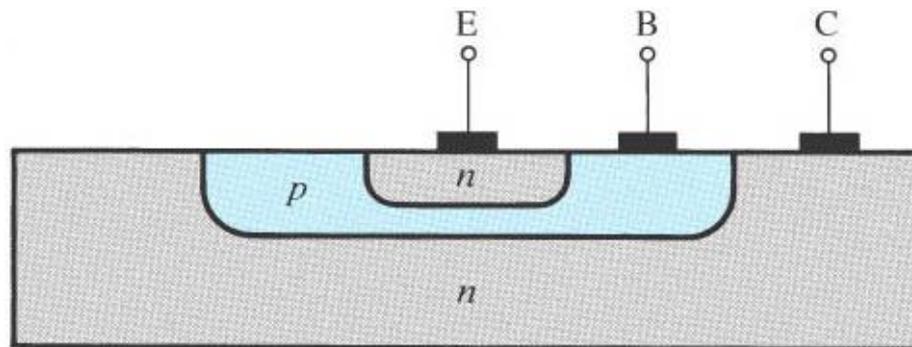


Figure 1. Cross-section of an *npn* BJT.

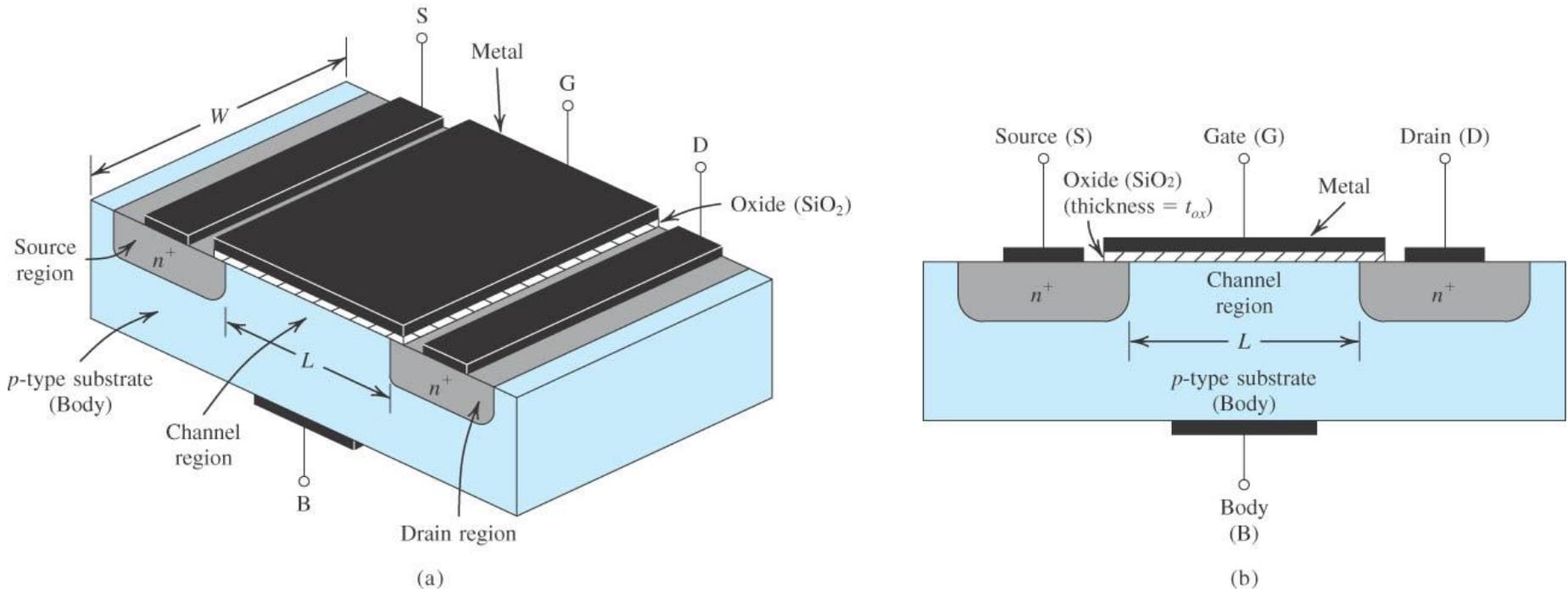


Figure 2. Physical structure of the enhancement-type NMOS transistor: **(a)** perspective view; **(b)** cross-section. Typically $L = 0.1$ to $3 \mu\text{m}$, $W = 0.2$ to $100 \mu\text{m}$, and the thickness of the oxide layer (t_{ox}) is in the range of 2 to 50 nm.

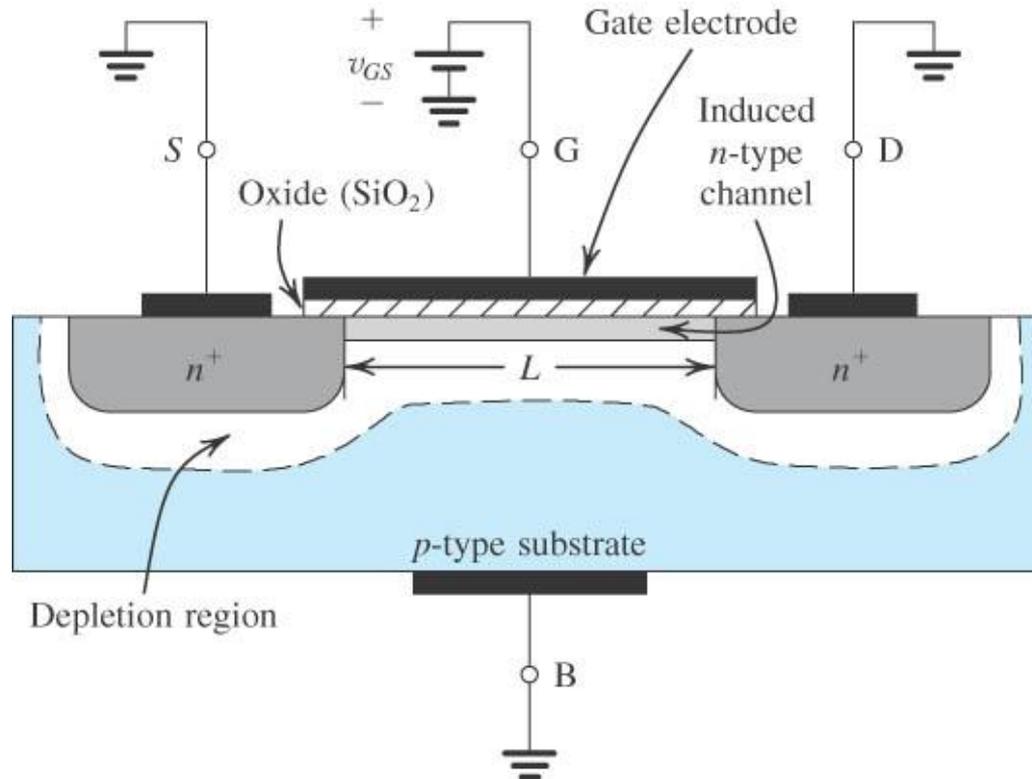
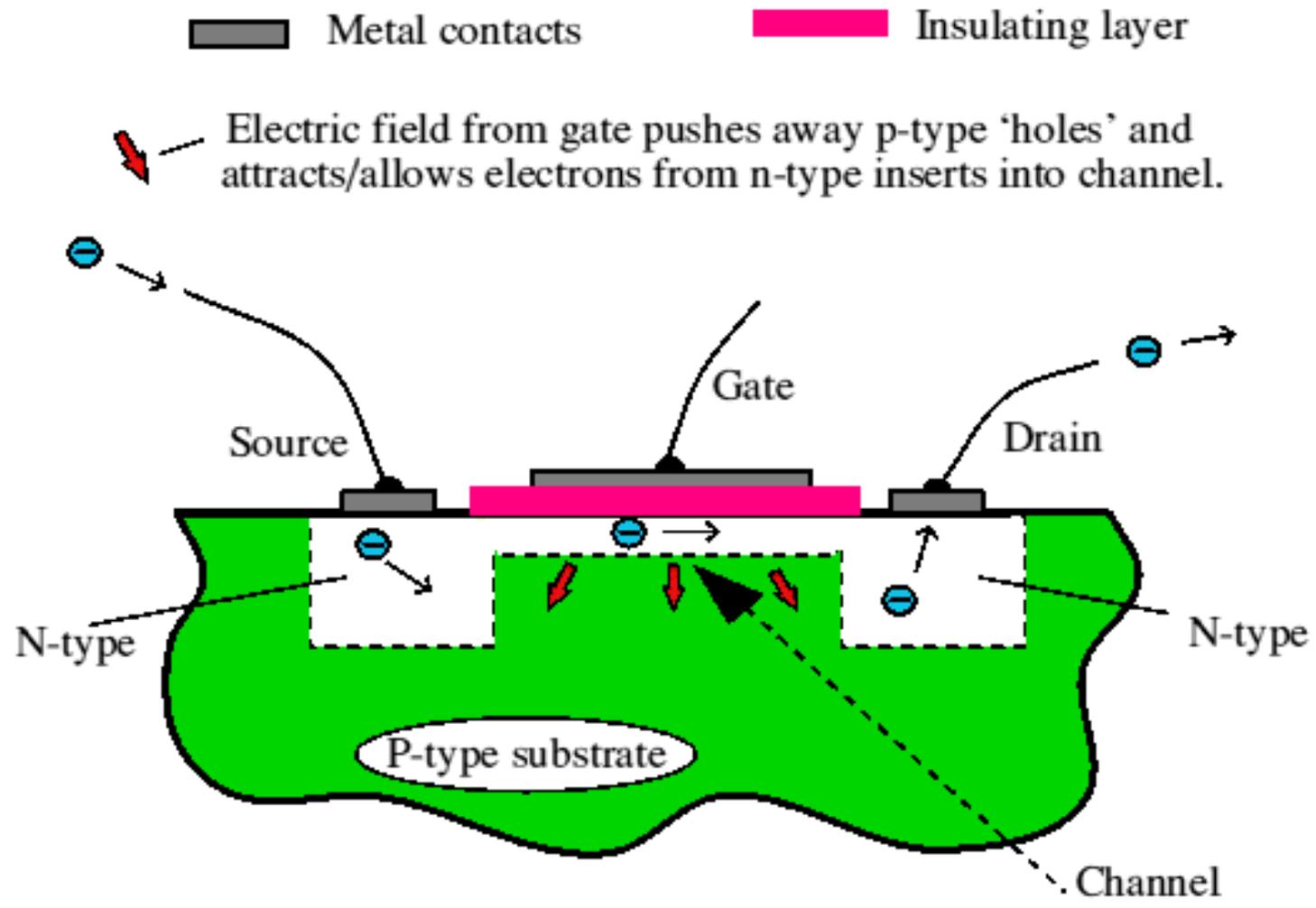


Figure 3. The enhancement-type NMOS transistor with a positive voltage applied to the gate. An *n* channel is induced at the top of the substrate beneath the gate.



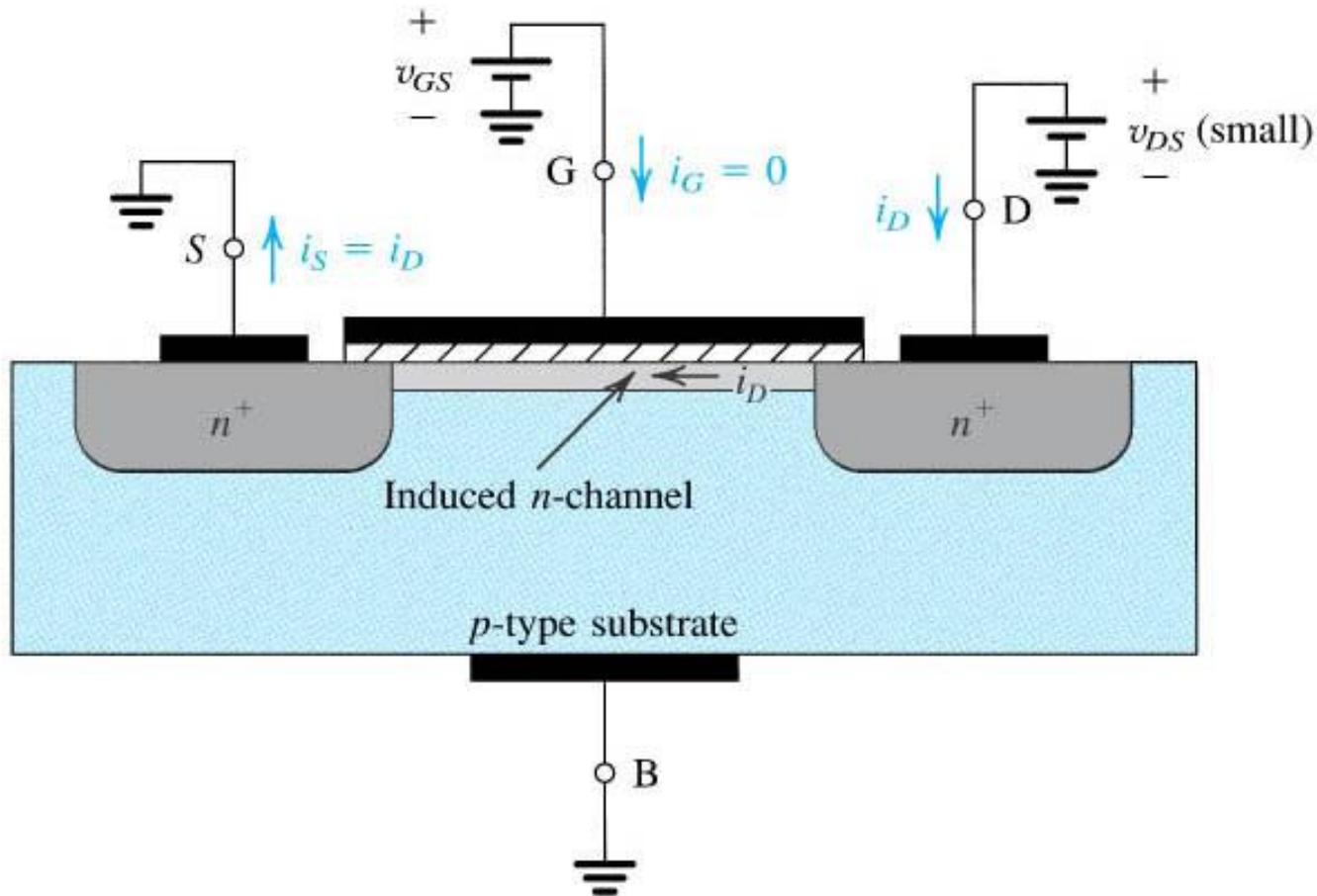


Figure 4. An NMOS transistor with $v_{GS} > V_t$ and with a small v_{DS} applied. The device acts as a resistance whose value is determined by v_{GS} . Specifically, the channel conductance is proportional to $v_{GS} - V_t$ and thus i_D is proportional to $(v_{GS} - V_t) v_{DS}$. Note that the depletion region is not shown (for simplicity).

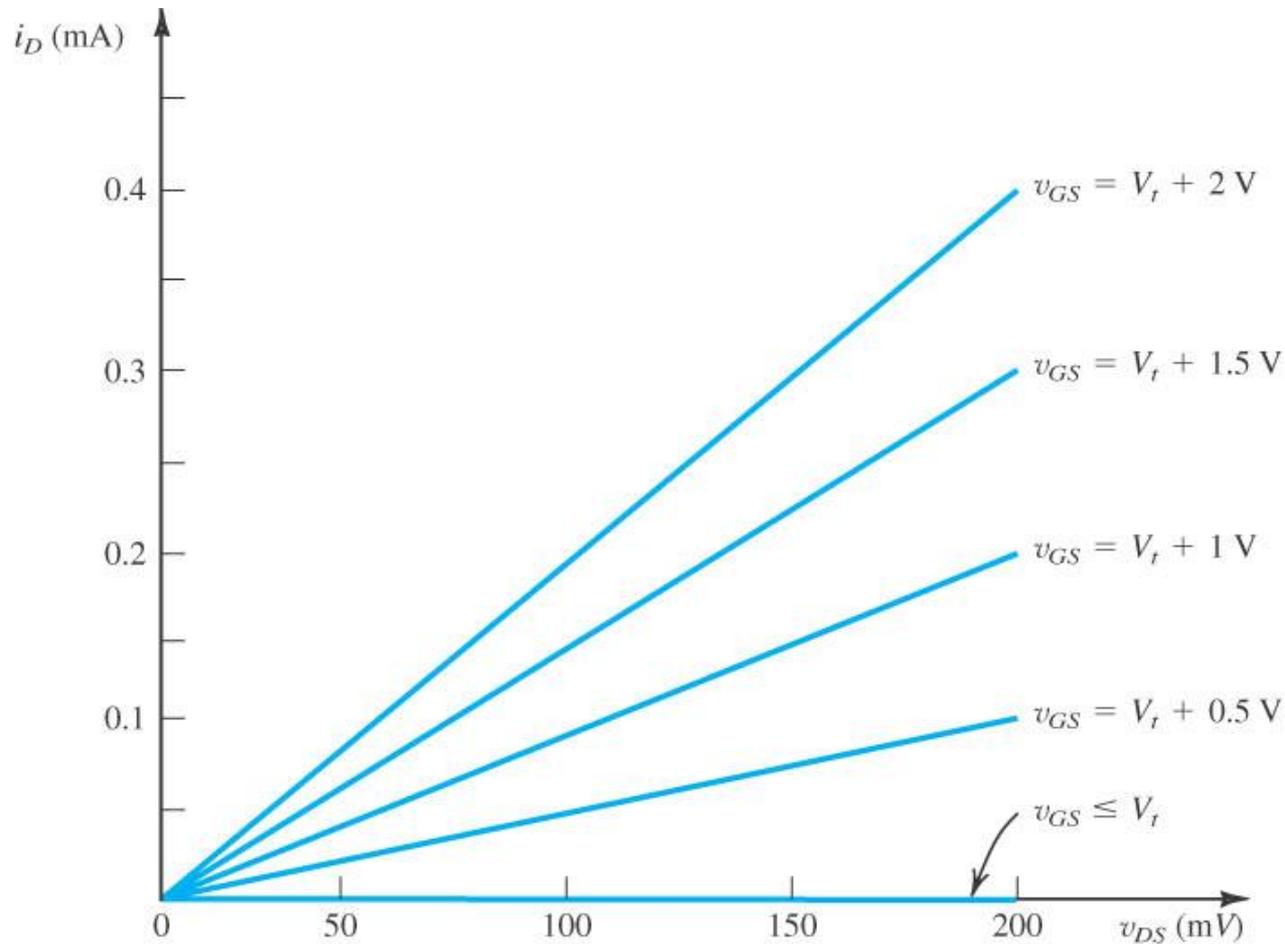


Figure 5. The i_D - v_{DS} characteristics of the MOSFET in Fig. 4.3 when the voltage applied between drain and source, v_{DS} , is kept small. The device operates as a linear resistor whose value is controlled by v_{GS} .

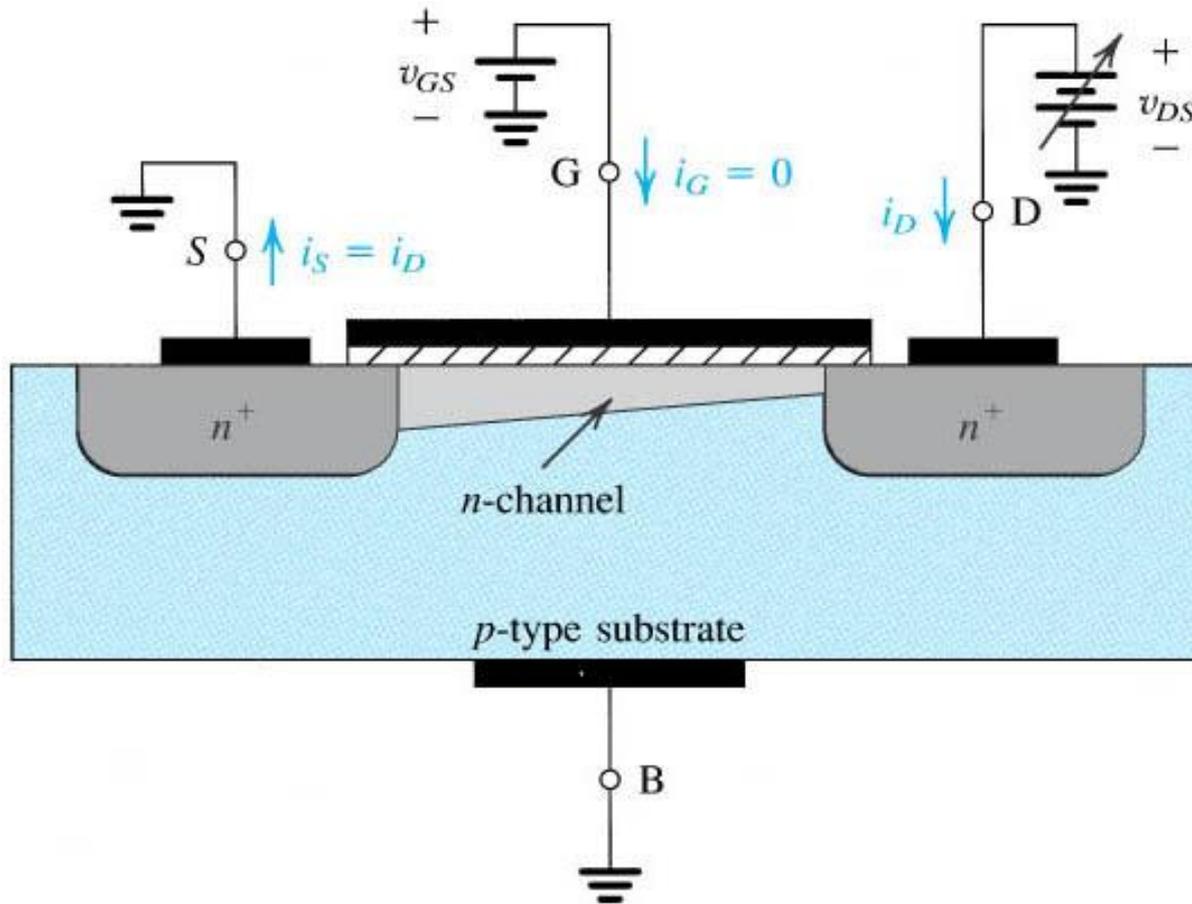


Figure 6. Operation of the enhancement NMOS transistor as v_{DS} is increased. The induced channel acquires a tapered shape, and its resistance increases as v_{DS} is increased. Here, v_{GS} is kept constant at a value $> V_T$.

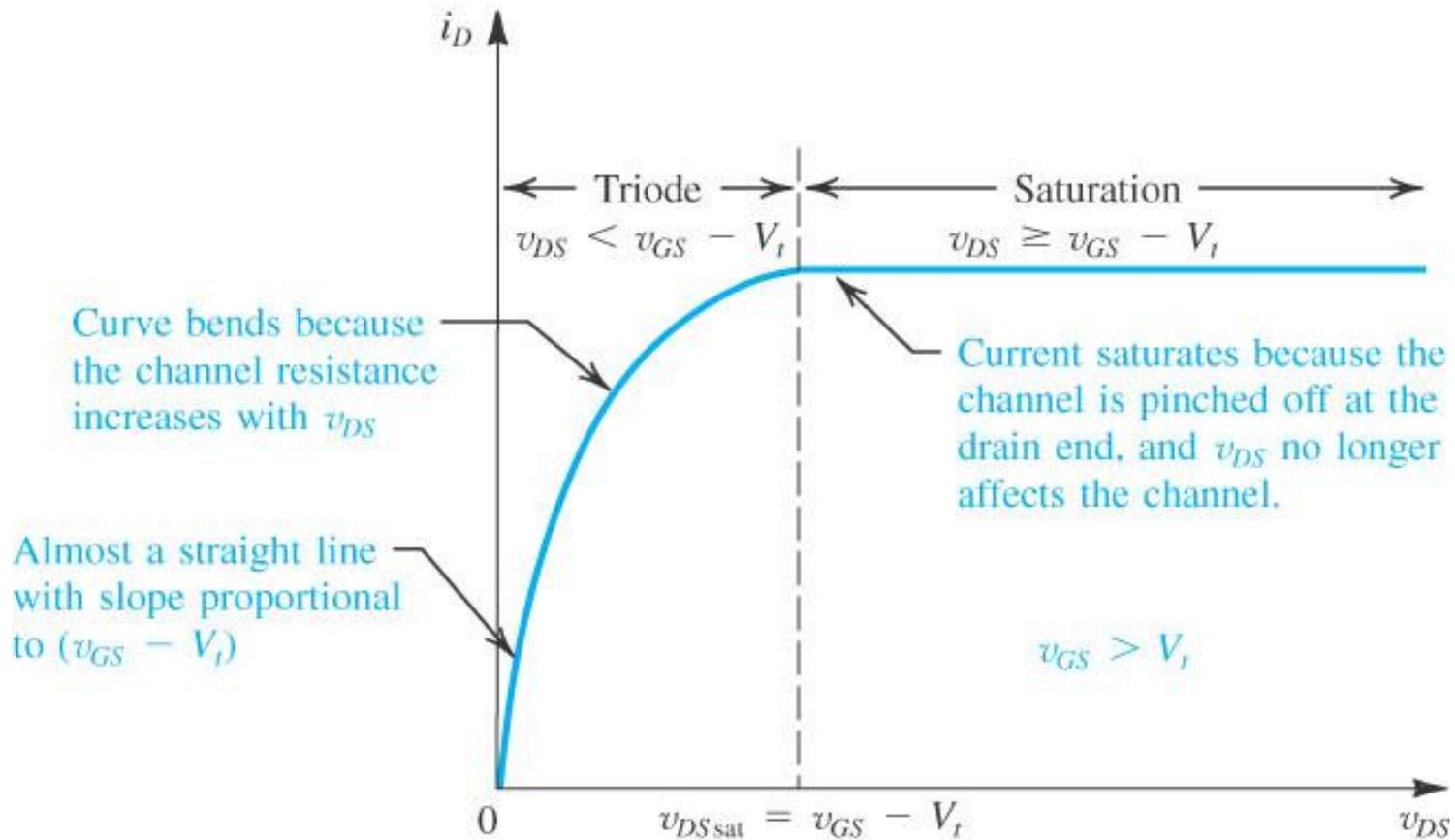


Figure 7. The drain current i_D versus the drain-to-source voltage v_{DS} for an enhancement-type NMOS transistor operated with $v_{GS} > V_t$.

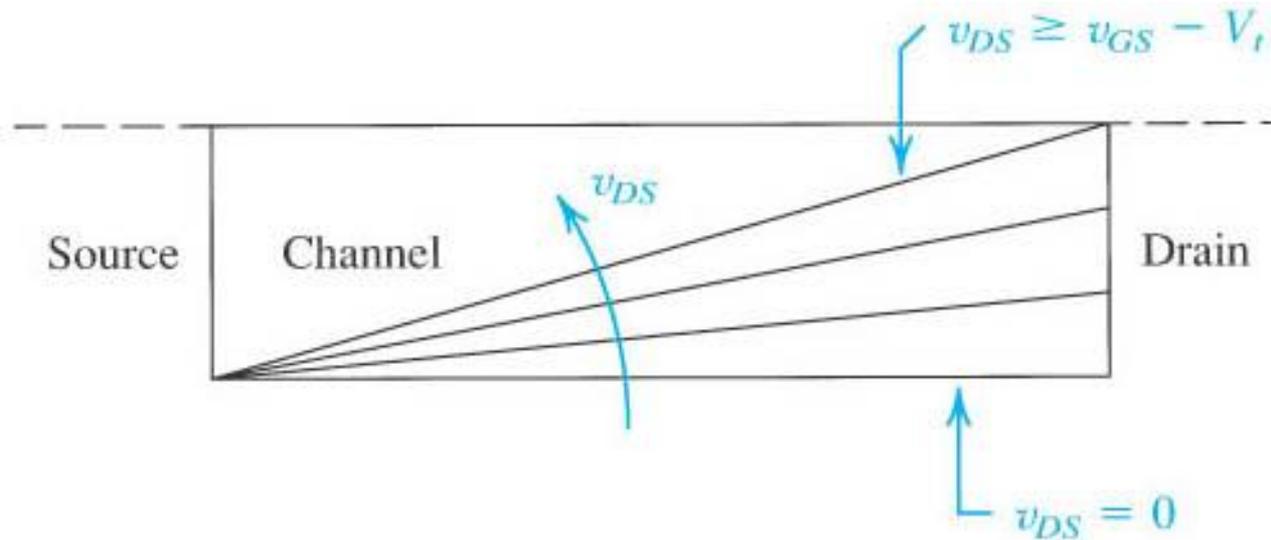


Figure 8. Increasing v_{DS} causes the channel to acquire a tapered shape. Eventually, as v_{DS} reaches $v_{GS} - V_t$ the channel is pinched off at the drain end. Increasing v_{DS} above $v_{GS} - V_t$ has little effect (theoretically, no effect) on the channel's shape.

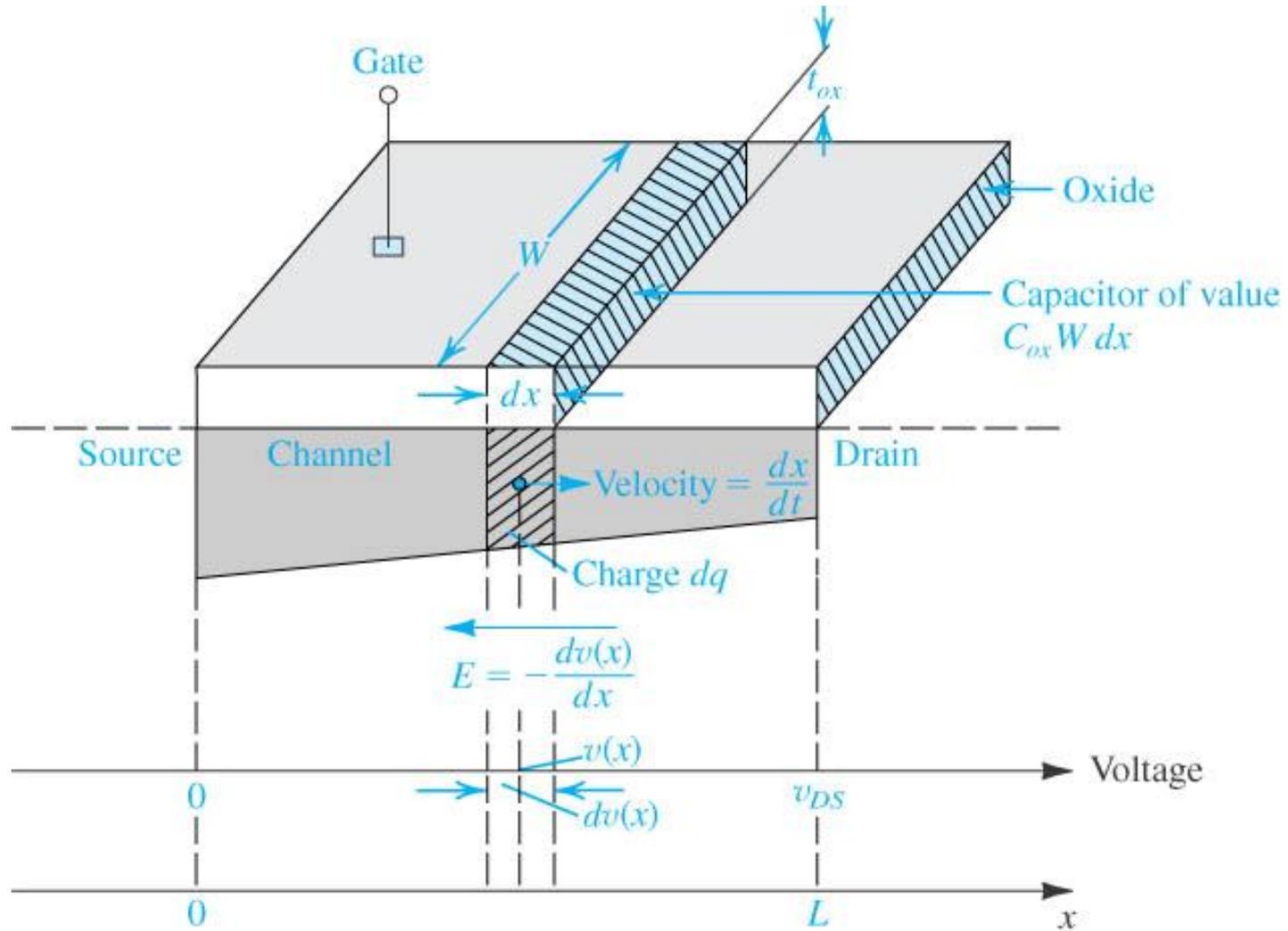
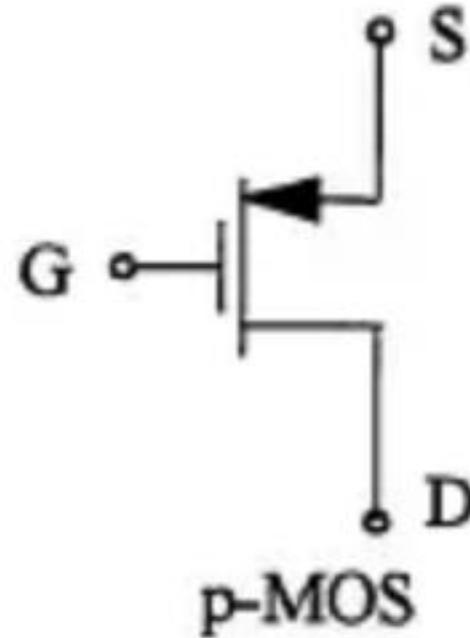
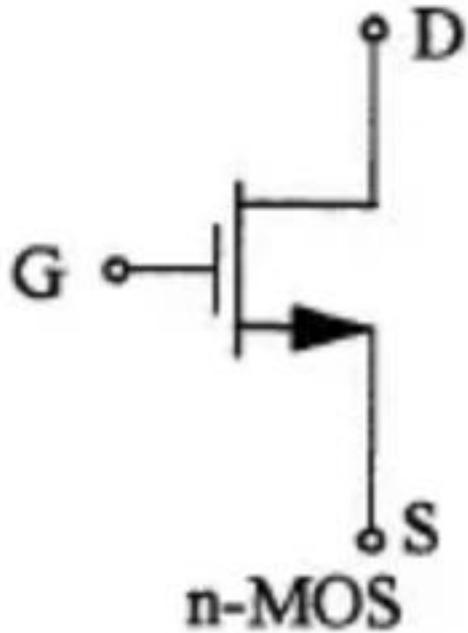


Figure 9. Derivation of the i_D-v_{DS} characteristic of the NMOS transistor.



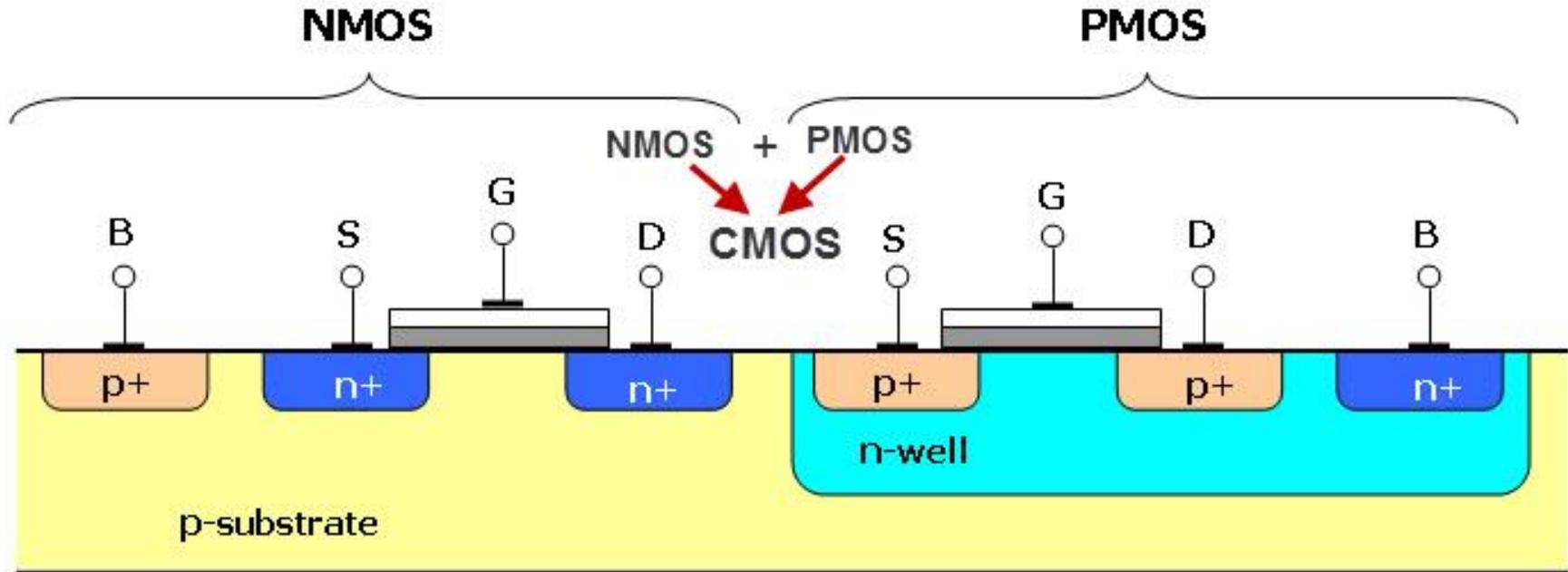


Figure 10. Cross-section of a CMOS integrated circuit. Note that the PMOS transistor is formed in a separate *n*-type region, known as an *n* well. Another arrangement is also possible in which an *n*-type body is used and the *n* device is formed in a *p* well. Not shown are the connections made to the *p*-type body and to the *n* well; the latter functions as the body terminal for the *p*-channel device.

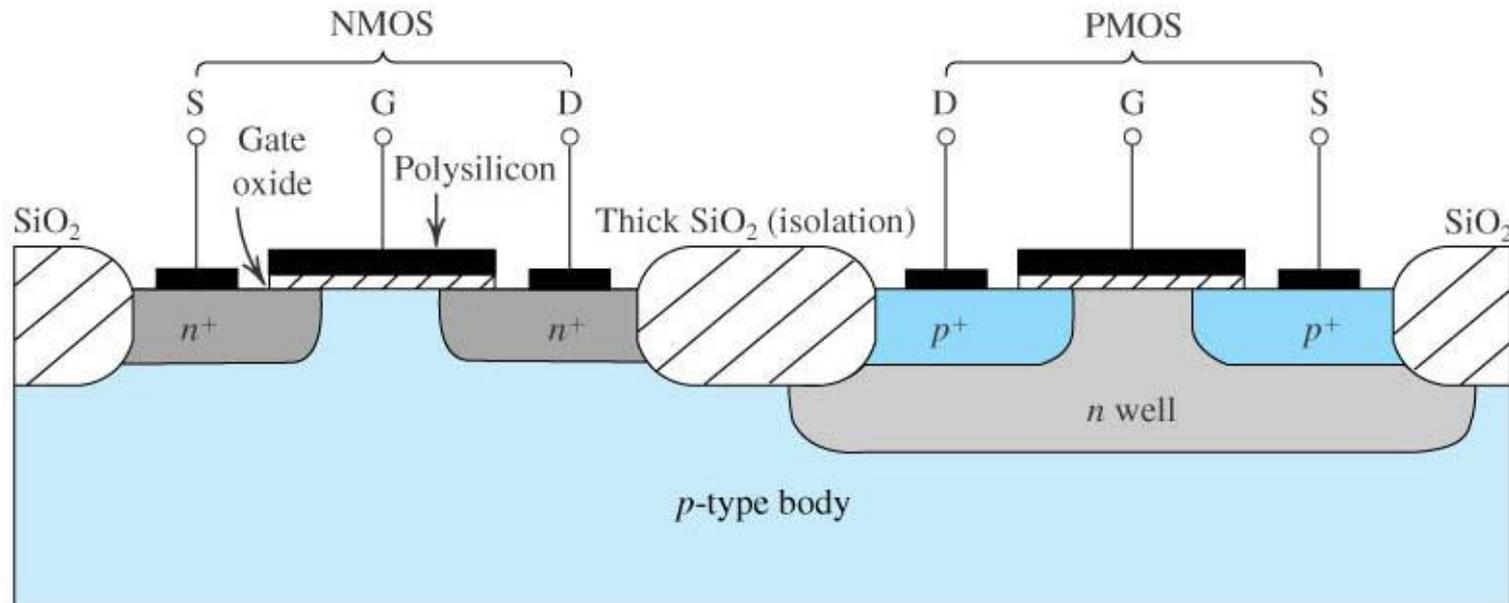
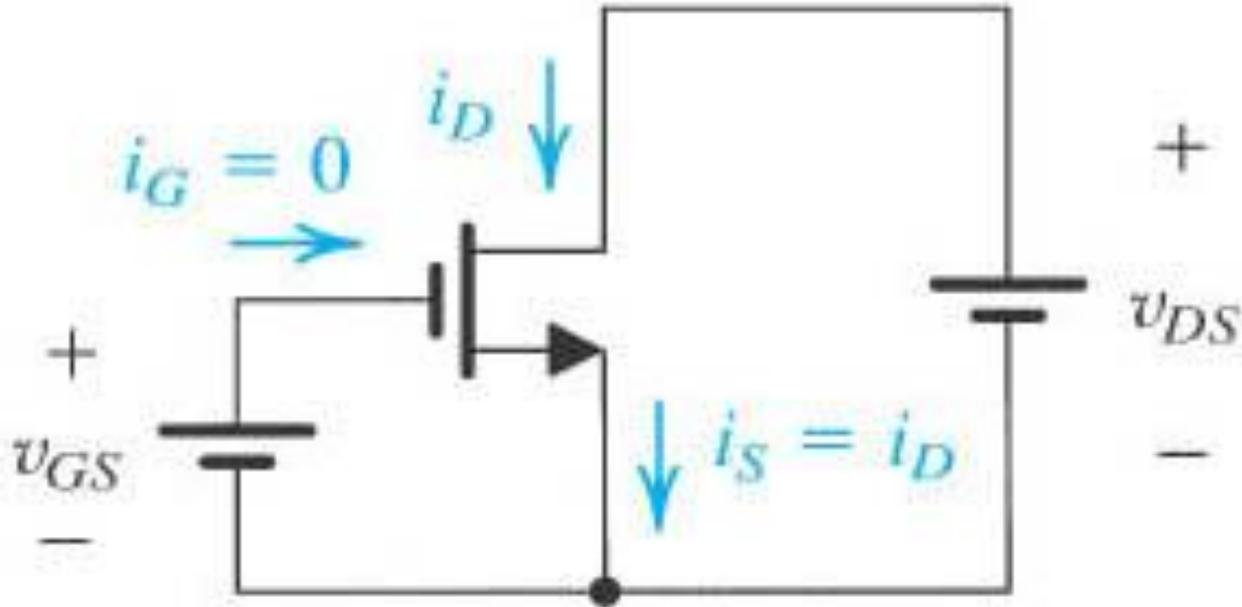


Figure 11. Cross-section of a CMOS integrated circuit. Note that the PMOS transistor is formed in a separate n -type region, known as an n well. Another arrangement is also possible in which an n -type body is used and the n device is formed in a p well. Not shown are the connections made to the p -type body and to the n well; the latter functions as the body terminal for the p -channel device.



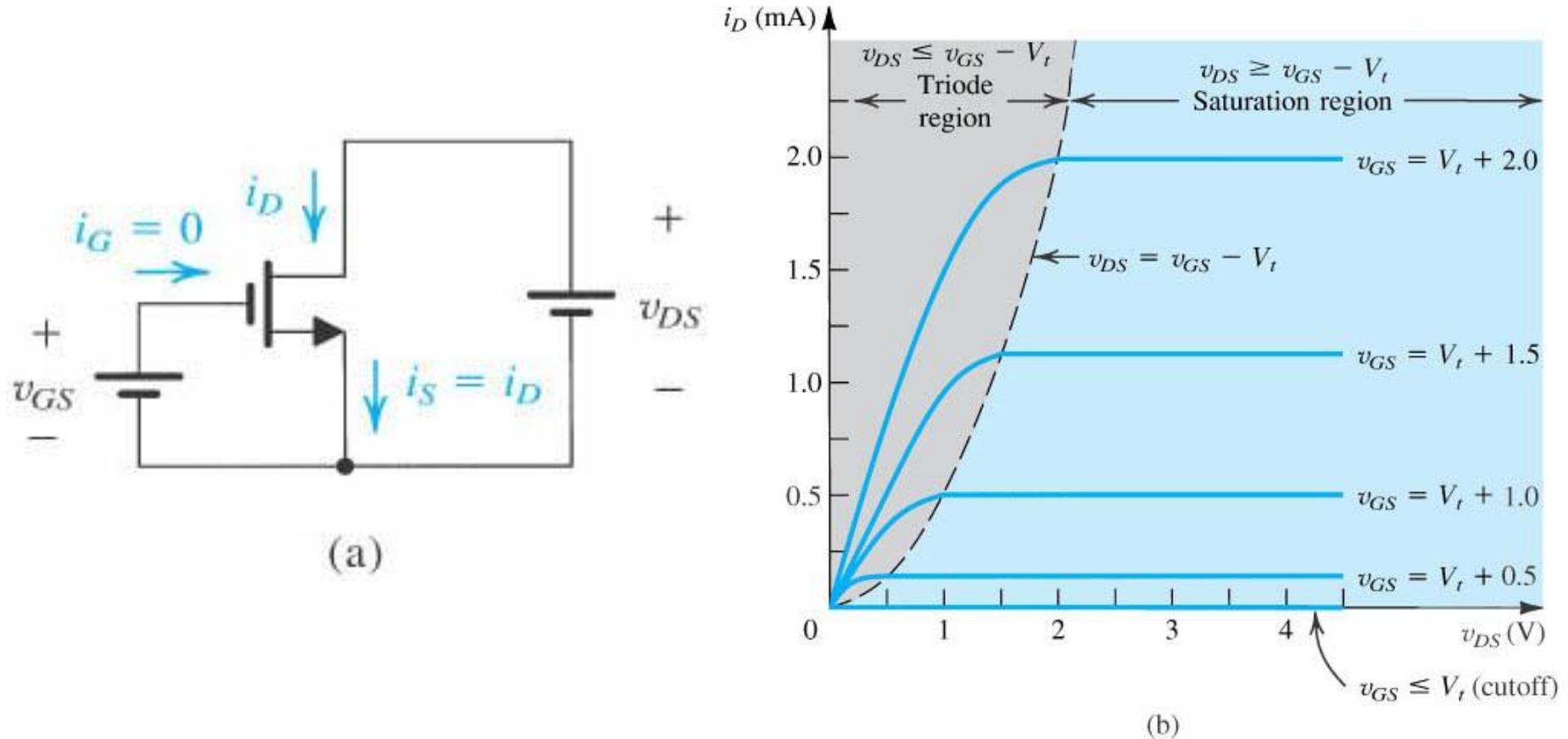


Figure 12. (a) An n-channel enhancement-type MOSFET with v_{GS} and v_{DS} applied and with the normal directions of current flow indicated. (b) The i_D - v_{DS} characteristics for a device with $k'_n(W/L) = 1.0 \text{ mA/V}^2$.

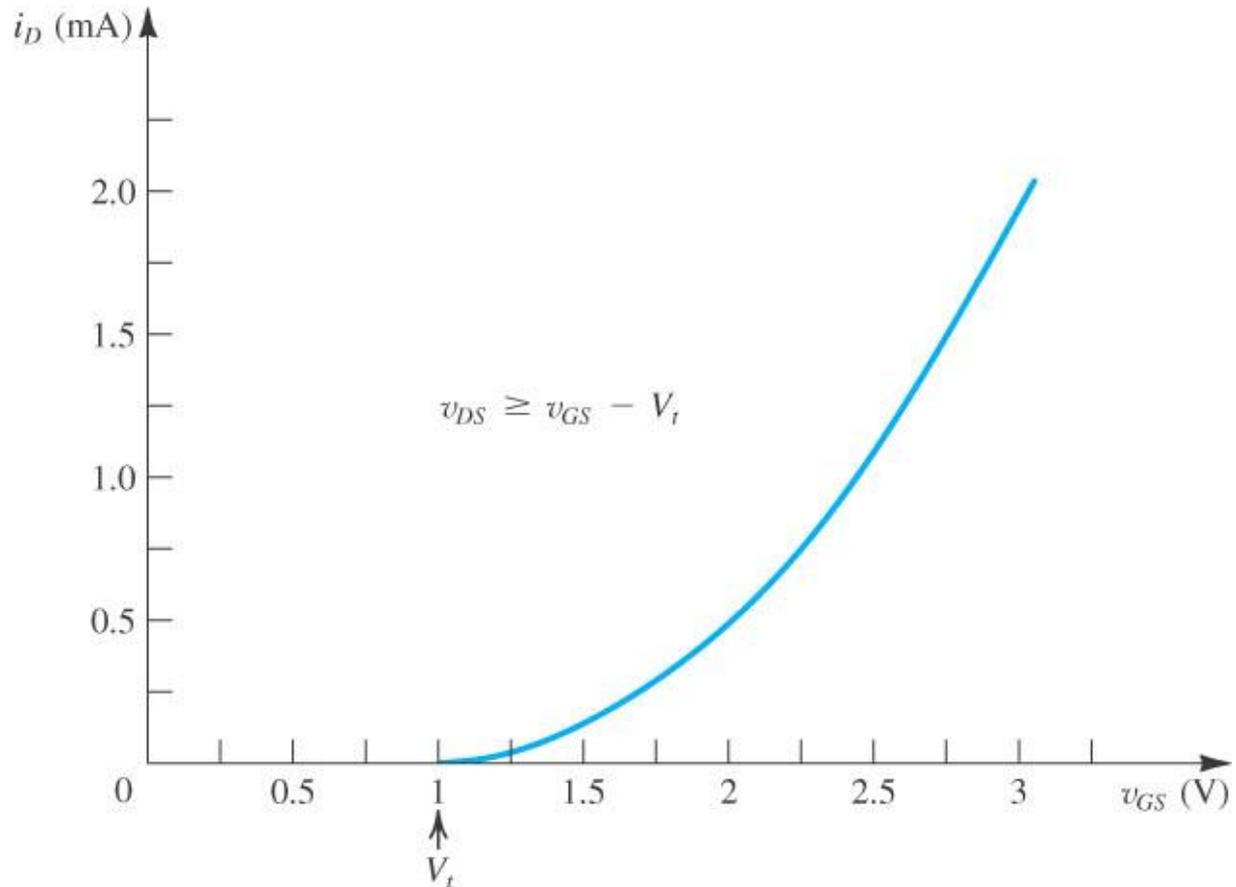


Figure 13. The i_D - v_{GS} characteristic for an enhancement-type NMOS transistor in saturation ($V_t = 1$ V, $k'_n W/L = 1.0$ mA/V²).

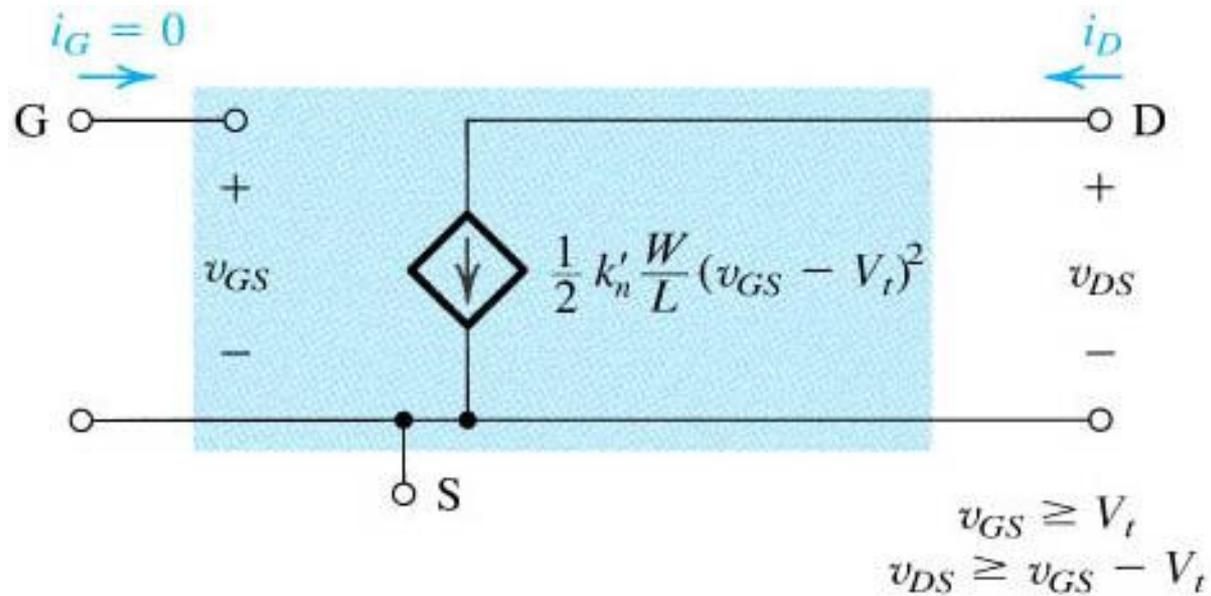


Figure 14. Large-signal equivalent-circuit model of an n -channel MOSFET operating in the saturation region.

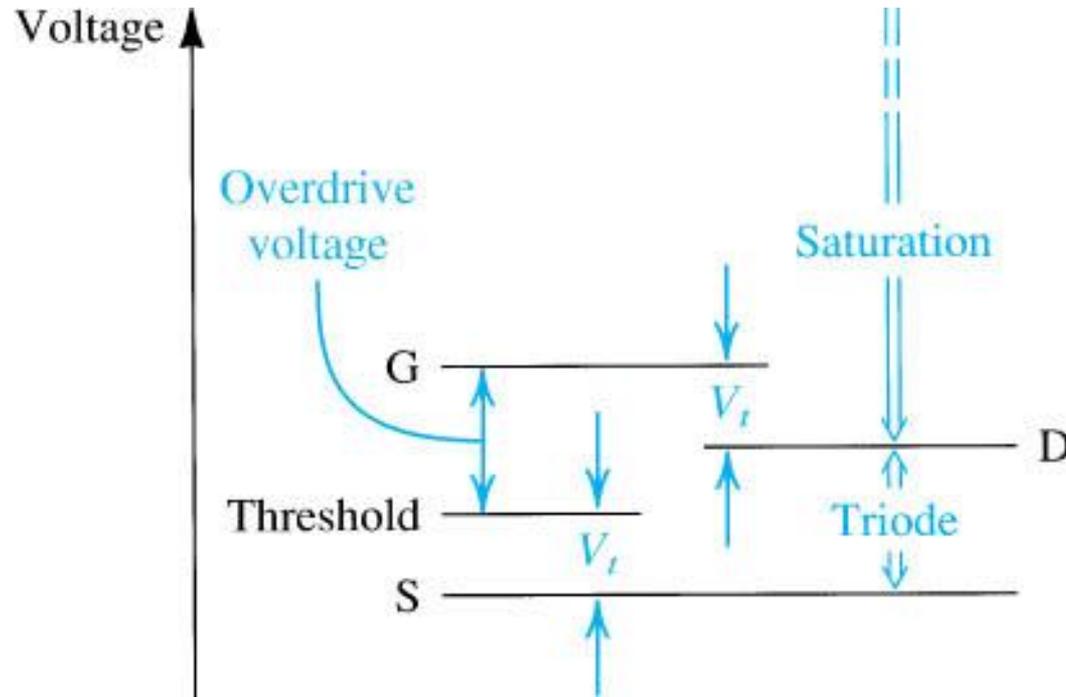
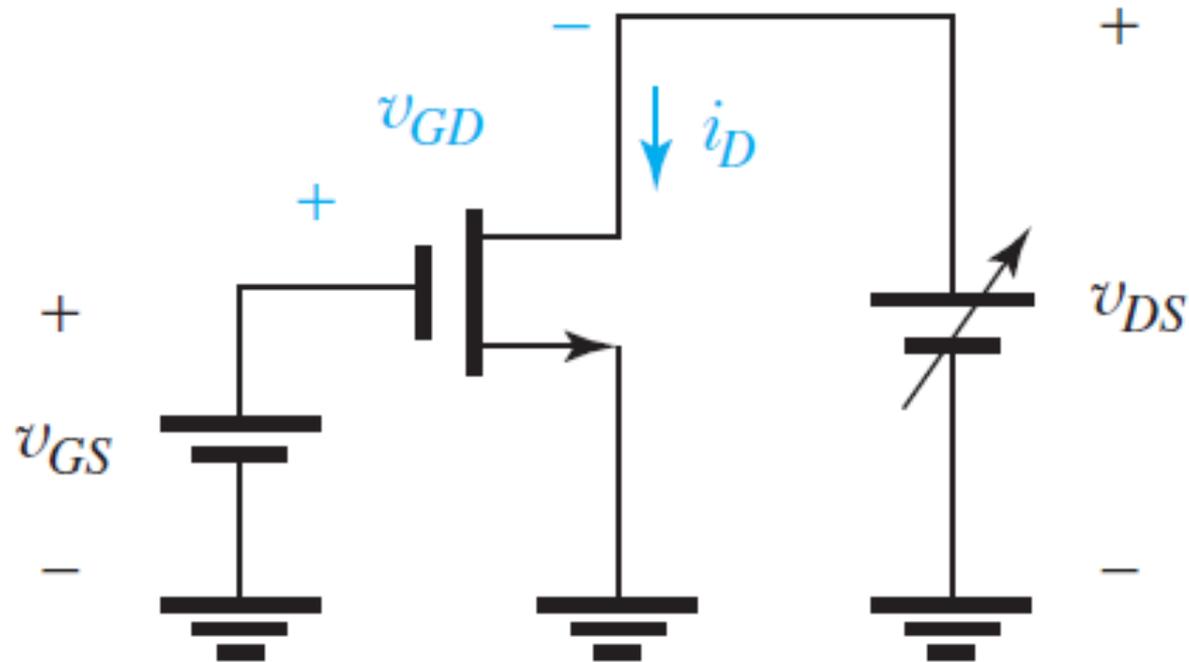
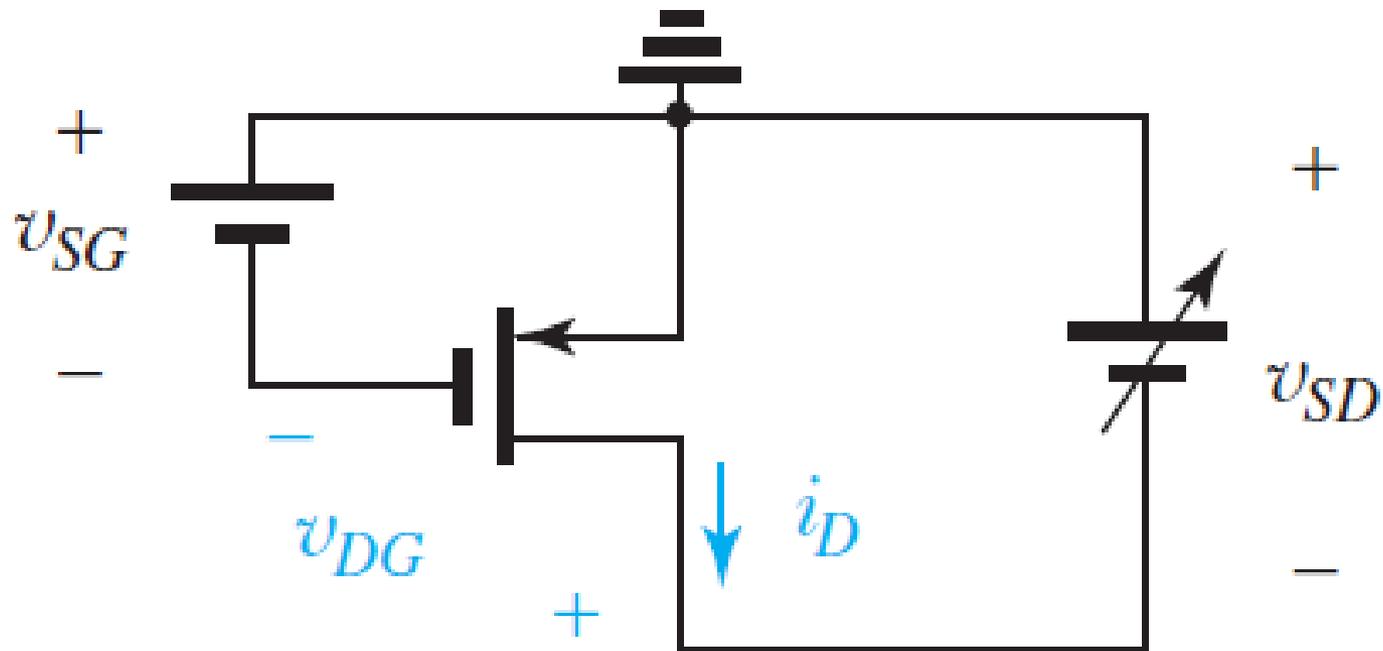


Figure 15. The relative levels of the terminal voltages of the enhancement NMOS transistor for operation in the triode region and in the saturation region.

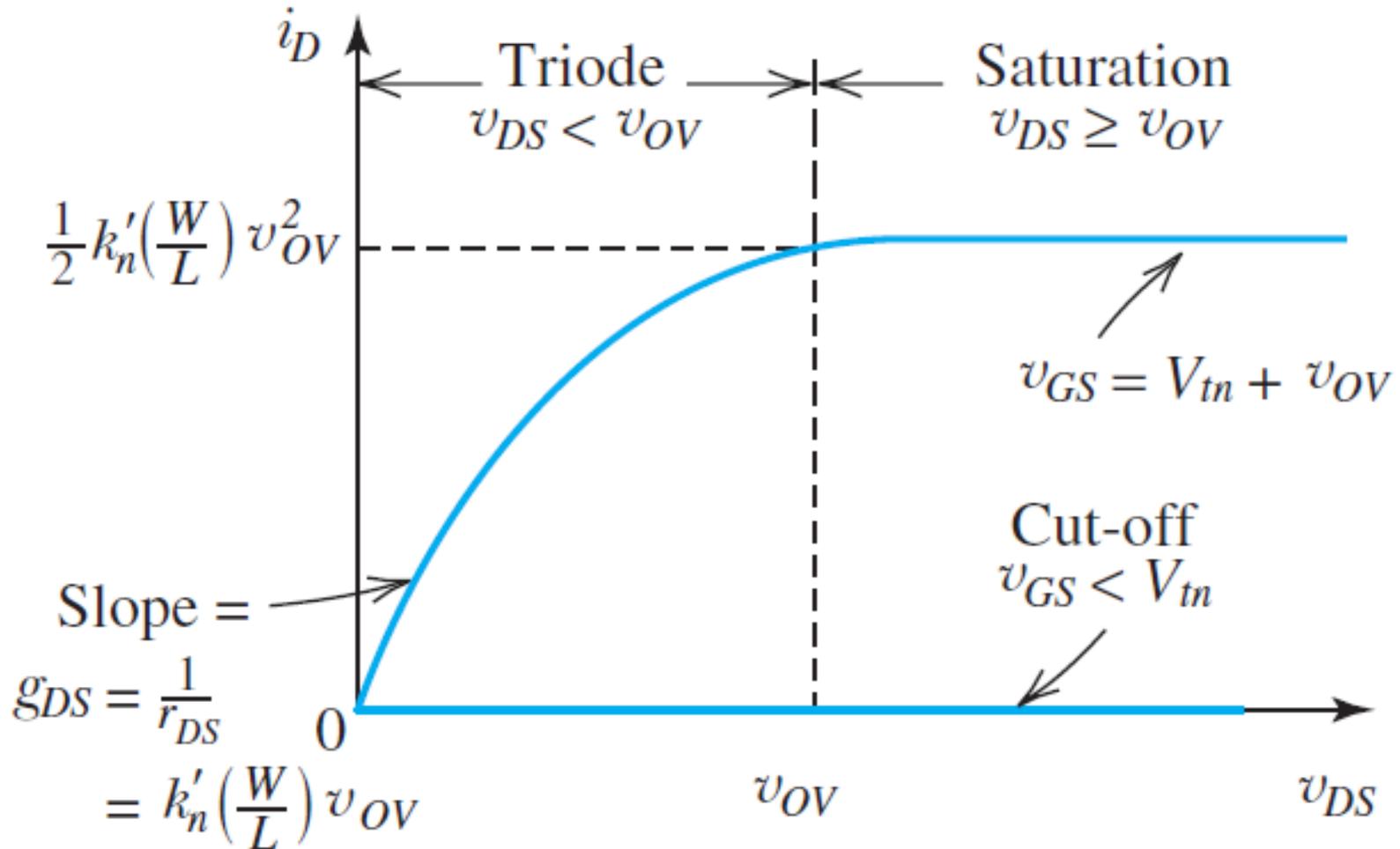
NMOS Transistor



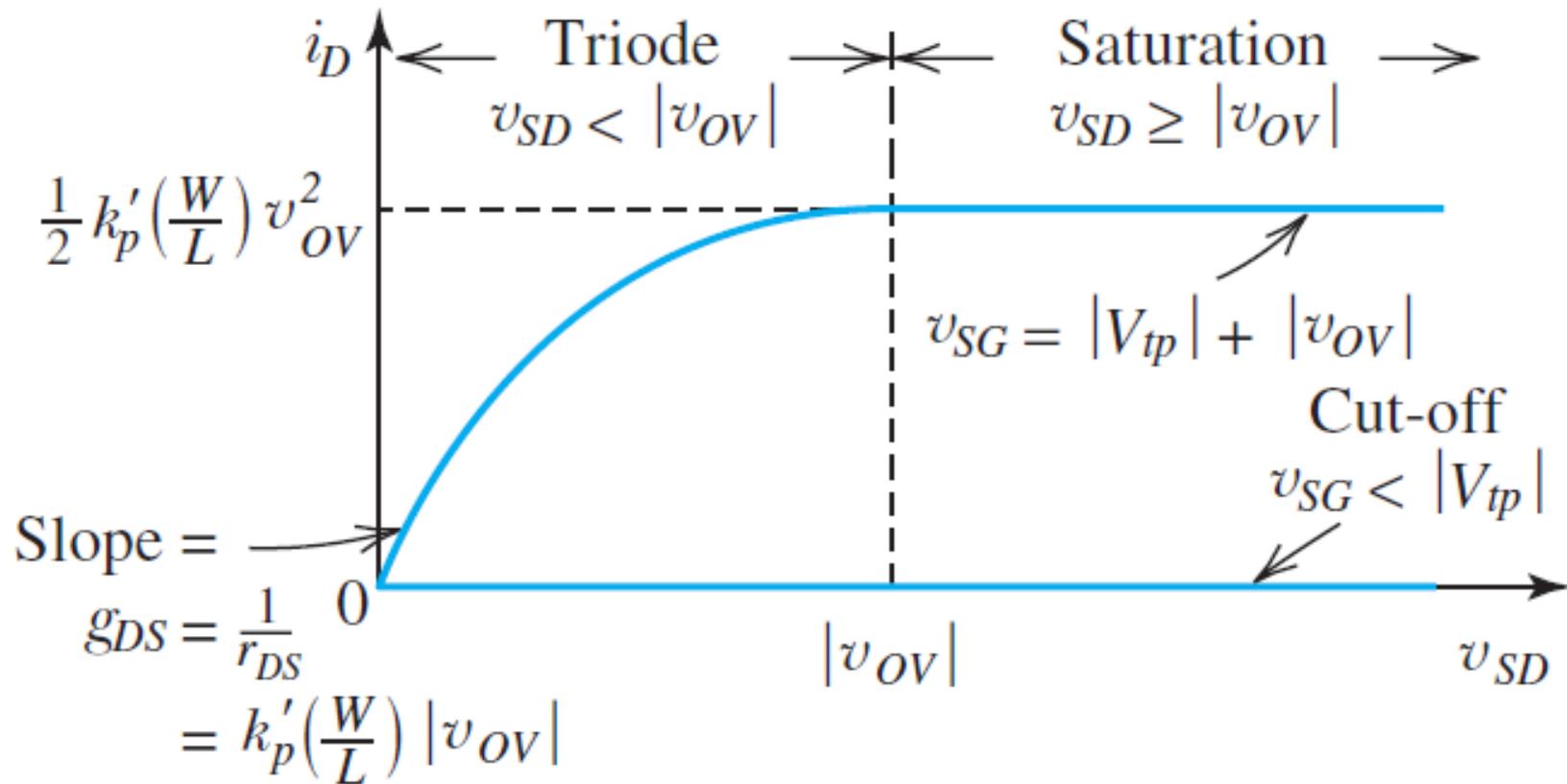
PMOS Transistor



NMOS Transistor



PMOS Transistor



For NMOS transistor :

$$V_{OV} = V_{GS} - V_{tn}$$

For PMOS transistor :

$$|V_{OV}| = V_{SG} - V_{tp}$$

Cut-off: $V_{GS} < V_T$

$$I_D = I_S = 0$$

Triode: $V_{GS} > V_T$ and $V_{DS} < V_{GS} - V_T$

$$I_D = k_n' (W/L) [(V_{GS} - V_T)V_{DS} - \frac{1}{2}V_{DS}^2]$$

Saturation: $V_{GS} > V_T$ and $V_{DS} > V_{GS} - V_T$

$$I_D = \frac{1}{2}k_n' (W/L)(V_{GS} - V_T)^2$$

where $k_n' = (\text{electron mobility}) \times (\text{gate capacitance})$

$$= \mu_n C_{ox} \quad \dots \text{electron velocity} = \mu_n E$$

and V_T depends on the doping concentration and gate material used

NMOS Transistor

Triode Region

Continuous channel, obtained by:

$$v_{GD} > V_{tn}$$

or equivalently:

$$v_{DS} < v_{OV}$$

Then,

$$i_D = k'_n \left(\frac{W}{L} \right) \left[(v_{GS} - V_{tn}) v_{DS} - \frac{1}{2} v_{DS}^2 \right]$$

or equivalently,

$$i_D = k'_n \left(\frac{W}{L} \right) \left(v_{OV} - \frac{1}{2} v_{DS} \right) v_{DS}$$

Saturation Region

Pinched-off channel, obtained by:

$$v_{GD} \leq V_{tn}$$

or equivalently:

$$v_{DS} \geq v_{OV}$$

Then

$$i_D = \frac{1}{2} k'_n \left(\frac{W}{L} \right) (v_{GS} - V_{tn})^2$$

or equivalently,

$$i_D = \frac{1}{2} k'_n \left(\frac{W}{L} \right) v_{OV}^2$$

PMOS Transistor

Triode Region

Continuous channel, obtained by:

$$v_{DG} > |V_{tp}|$$

or equivalently:

$$v_{SD} < |v_{OV}|$$

Then,

$$i_D = k'_p \left(\frac{W}{L} \right) \left[(v_{SG} - |V_{tp}|) v_{SD} - \frac{1}{2} v_{SD}^2 \right]$$

or equivalently

$$i_D = k'_p \left(\frac{W}{L} \right) \left(|v_{OV}| - \frac{1}{2} v_{SD} \right) v_{SD}$$

Saturation Region

Pinched-off channel, obtained by:

$$v_{DG} \leq |V_{tp}|$$

or equivalently

$$v_{SD} \geq |v_{OV}|$$

Then

$$i_D = \frac{1}{2} k'_p \left(\frac{W}{L} \right) (v_{SG} - |V_{tp}|)^2$$

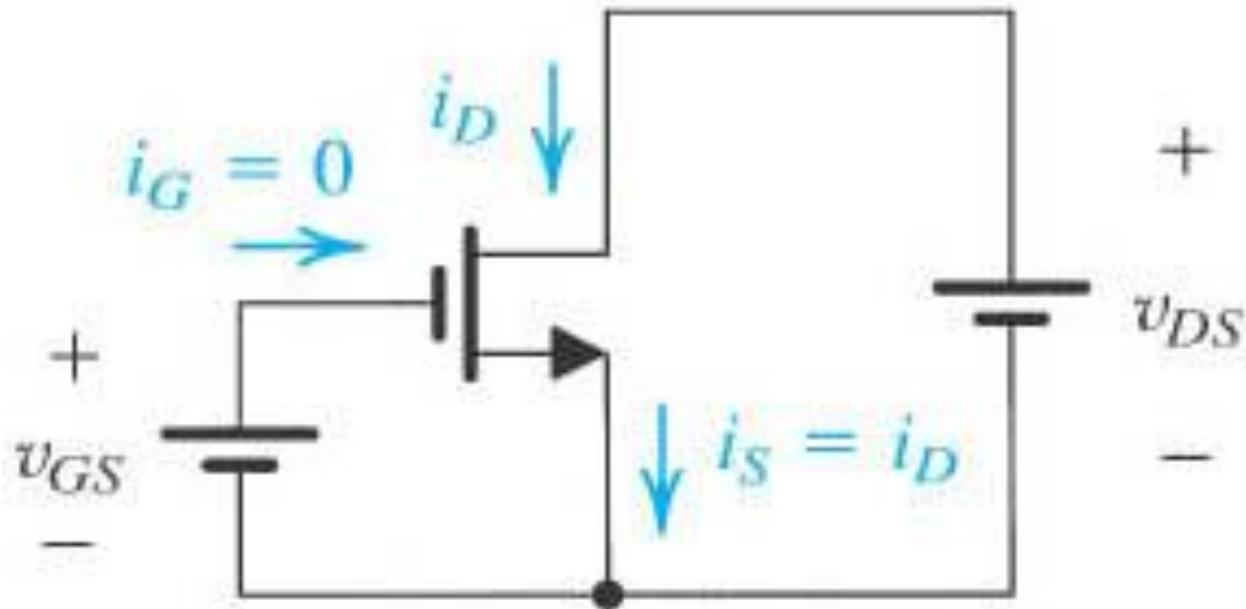
or equivalently

$$i_D = \frac{1}{2} k'_p \left(\frac{W}{L} \right) v_{OV}^2$$

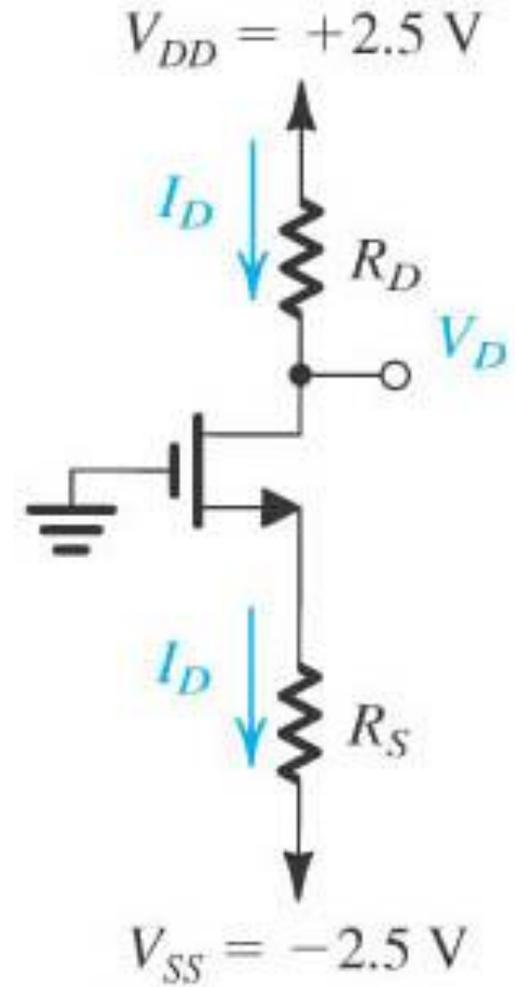
Consider an NMOS transistor with $V_t = 0.7$ V, $k_n' = 194 \mu\text{A}/\text{V}^2$, $W = 8 \mu\text{m}$, and $L = 0.8 \mu\text{m}$.

- a. Calculate the values of V_{OV} , V_{GS} , and V_{DSmin} needed to operate the transistor in the saturation region with a DC current $I_D = 100 \mu\text{A}$.
- b. Calculate the values of V_{DS} when V_{GS} remain constant that results in $I_D = 60 \mu\text{A}$.

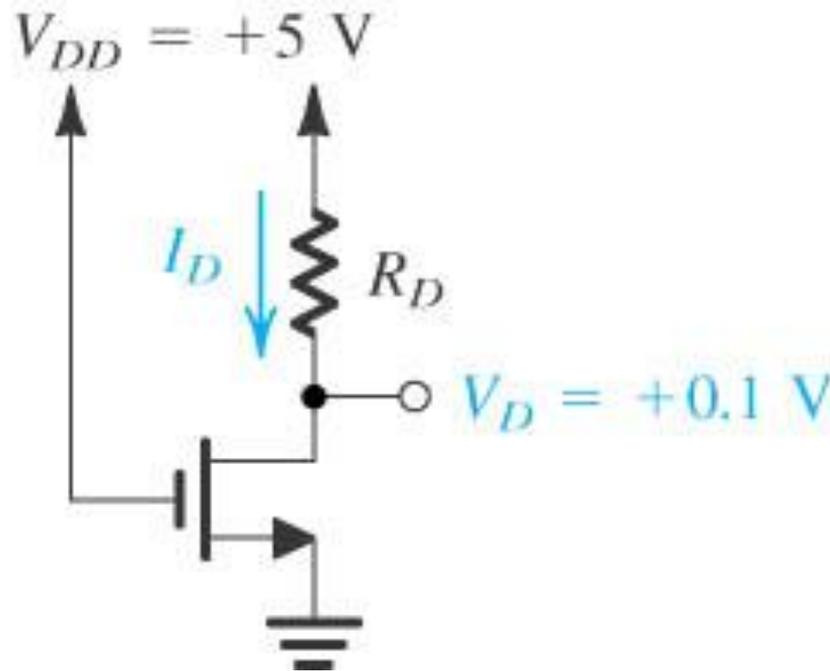
There are some ways to bias the MOSFET. The most common ways :



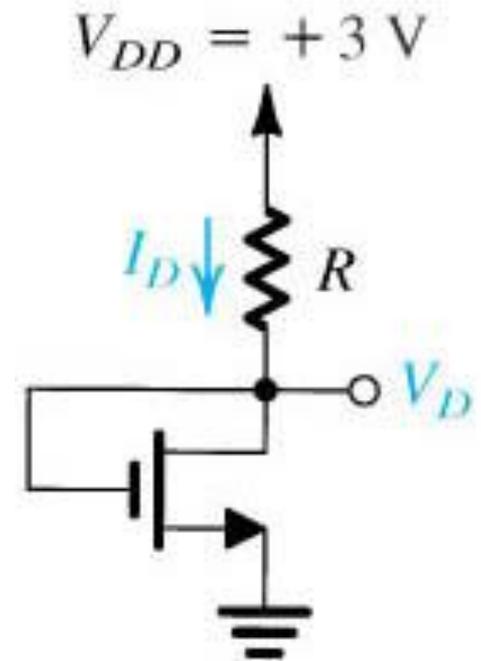
Determine the values of R_D and R_S so that the transistor operates at $I_D = 0.4$ mA and $V_D = +0.5$ V. The NMOS transistor has $V_t = 0.7$ V, $\mu_n C_{ox} = 100$ $\mu\text{A}/\text{V}^2$, $L = 1$ μm , and $W = 32$ μm .



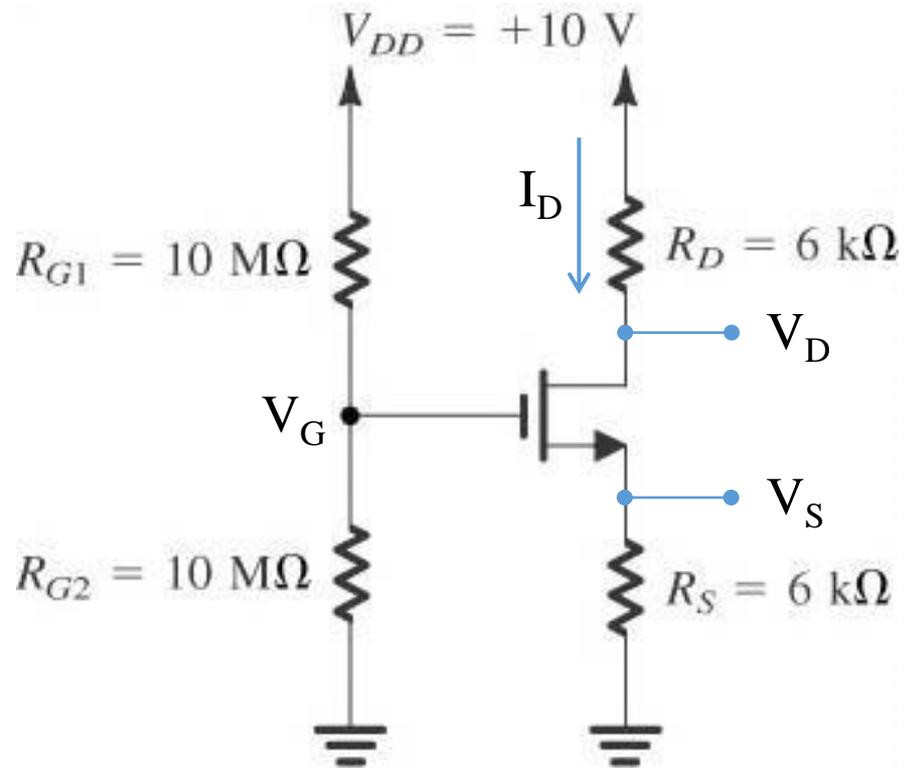
Determine the values of I_D and R_D to establish a drain voltage of 0.1 V. Knowing the NMOS transistor has $V_t = 1$ V and $k_n = 1$ mA/V².

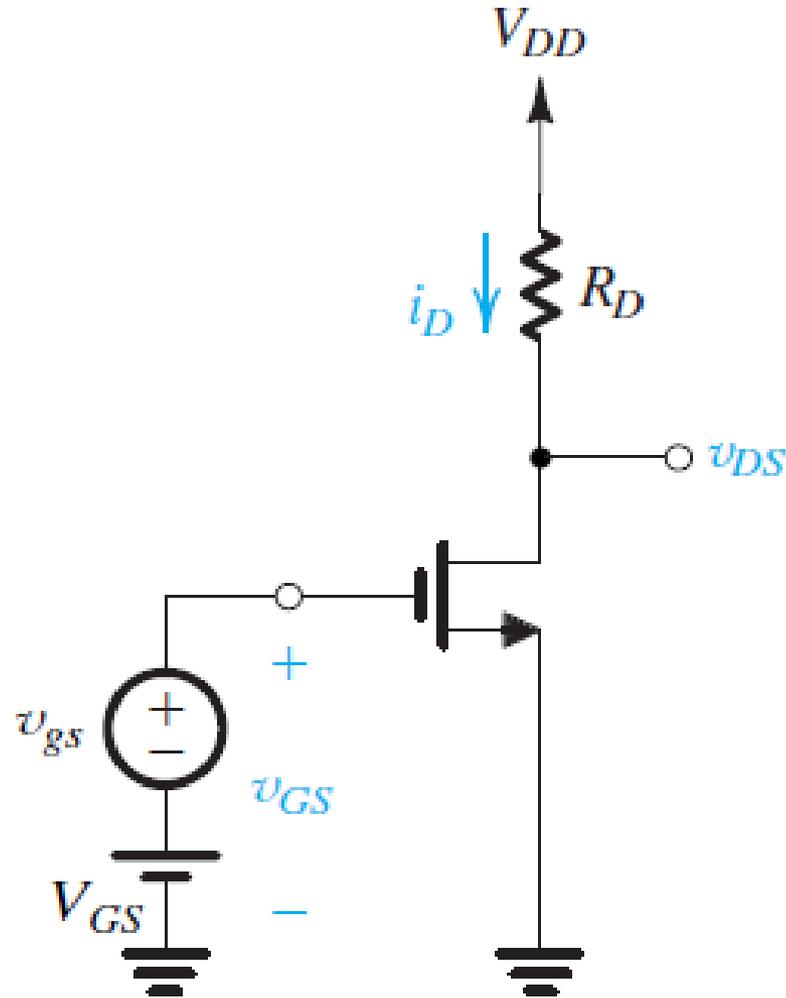


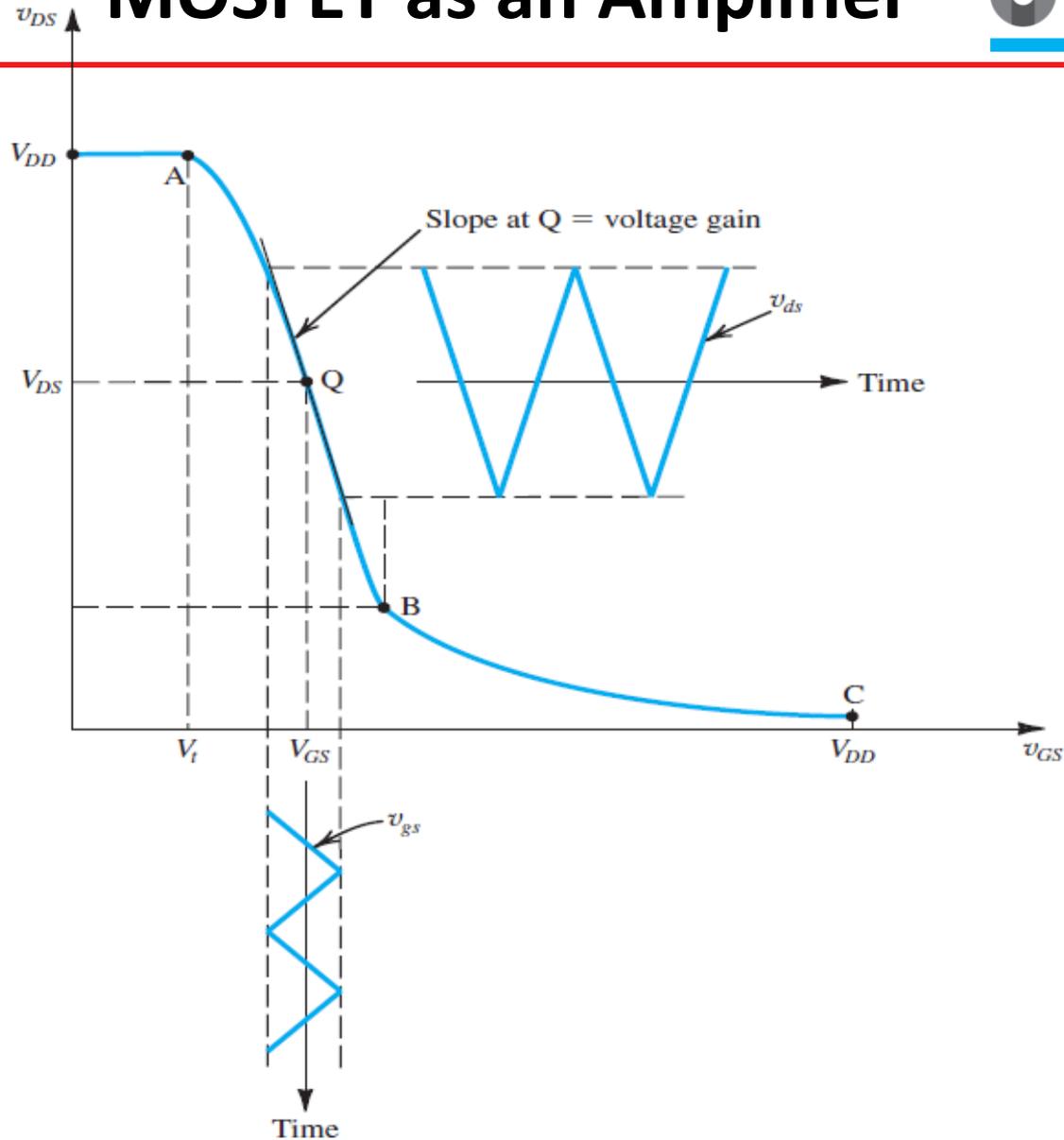
Determine the values of R so that the transistor operates at $V_D = 0.8$ V.
 Knowing the NMOS transistor has $V_t = 0.5$ V and $k_n = 1.6$ mA/V².



Determine the values of I_D , V_D , V_G , and V_S . The NMOS transistor has $V_t = 1 \text{ V}$, $k_n = 1 \text{ mA/V}^2$.







Jika diketahui:

$$V_t = 0.4 \text{ V},$$

$$k_n = 4 \text{ mA/V}^2,$$

$$V_{DD} = 1.8 \text{ V},$$

$$R_D = 17.5 \text{ k}\Omega,$$

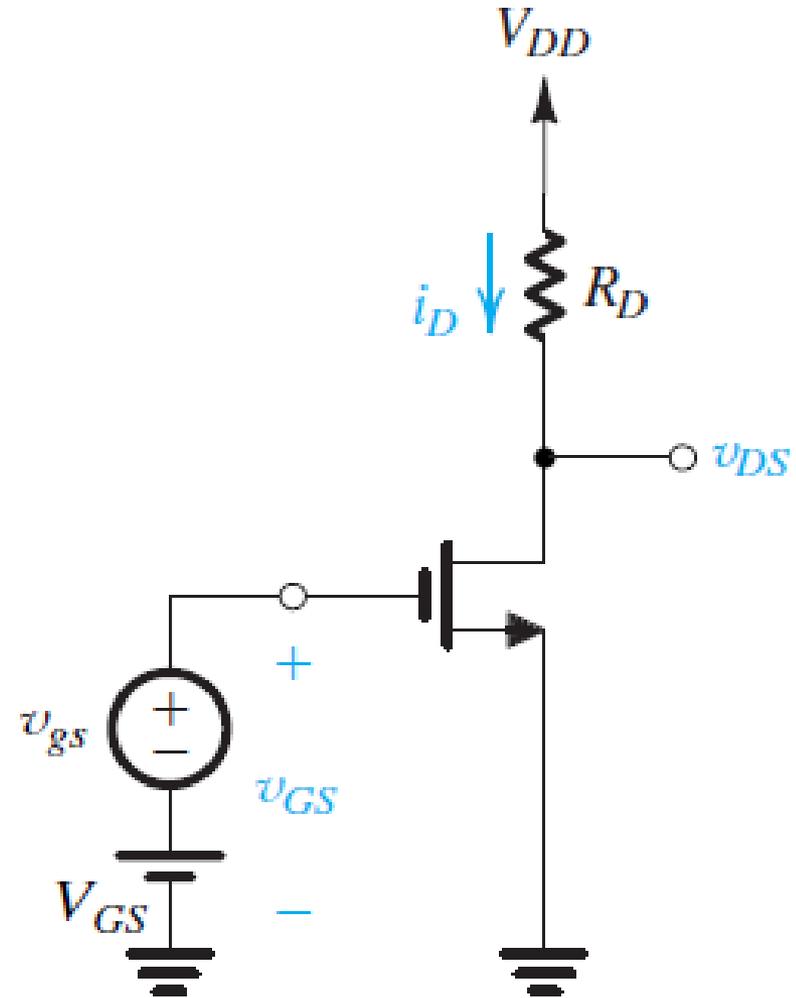
$$V_{GS} = 0.6 \text{ V},$$

a. Tentukan V_{OV} , I_D , dan V_{DS} , jika

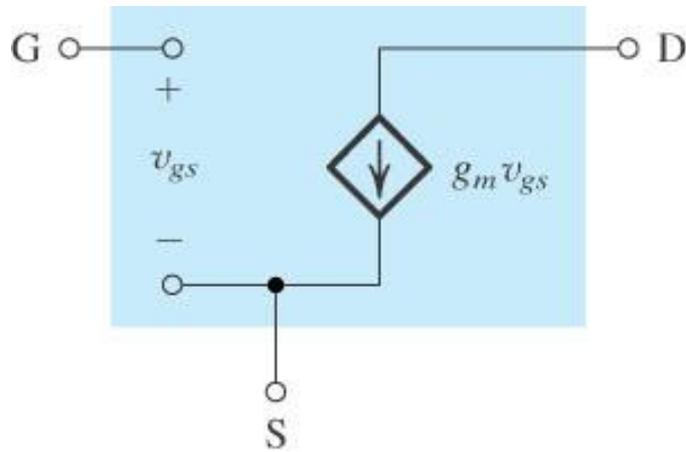
$$v_{gs} = 0 \text{ V}$$

b. Hitung kembali V_{DS} jika v_{gs} berubah sebesar $\pm 5 \text{ mV}$

c. Tentukan besar penguatan A_v

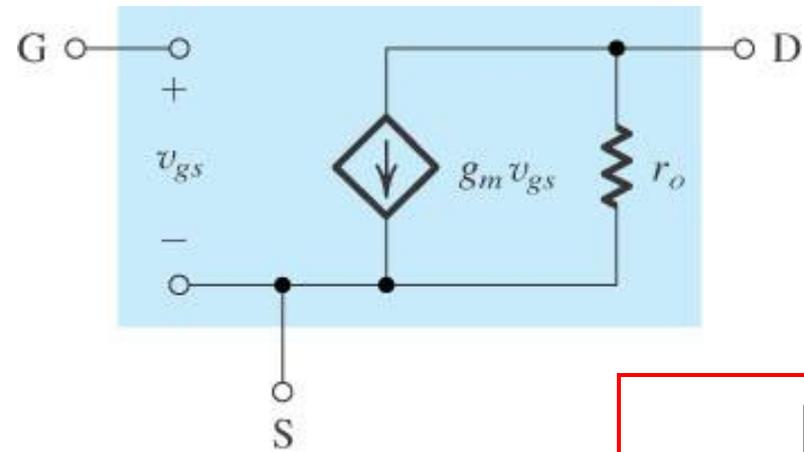


Jika tidak memiliki nilai V_A :



(a)

Jika memiliki nilai V_A :



(b)

$$r_o = \frac{|V_A|}{I_D}$$

$$\begin{aligned} g_m &= k_n' (W/L) (V_{GS} - V_t) = k_n V_{OV} \\ &= k_n V_{OV} \end{aligned}$$

1. Analisis rangkaian secara DC, (bila ada) kapasitor menjadi open-circuit.
2. Tentukan nilai V_G , V_S , V_D , dan I_D .
3. Tentukan nilai g_m dan r_o (bila ada).
4. Analisis rangkaian secara AC, sumber tegangan DC dan (bila ada) kapasitor menjadi short-circuit.
5. Ganti MOSFET dengan model pengganti sinyal kecil.
6. Tentukan nilai A_V (v_o / v_{gs}).

Jika diketahui:

$$V_t = 0.4 \text{ V}$$

$$k_n = 4 \text{ mA/V}^2$$

$$V_{DD} = 1.8 \text{ V}$$

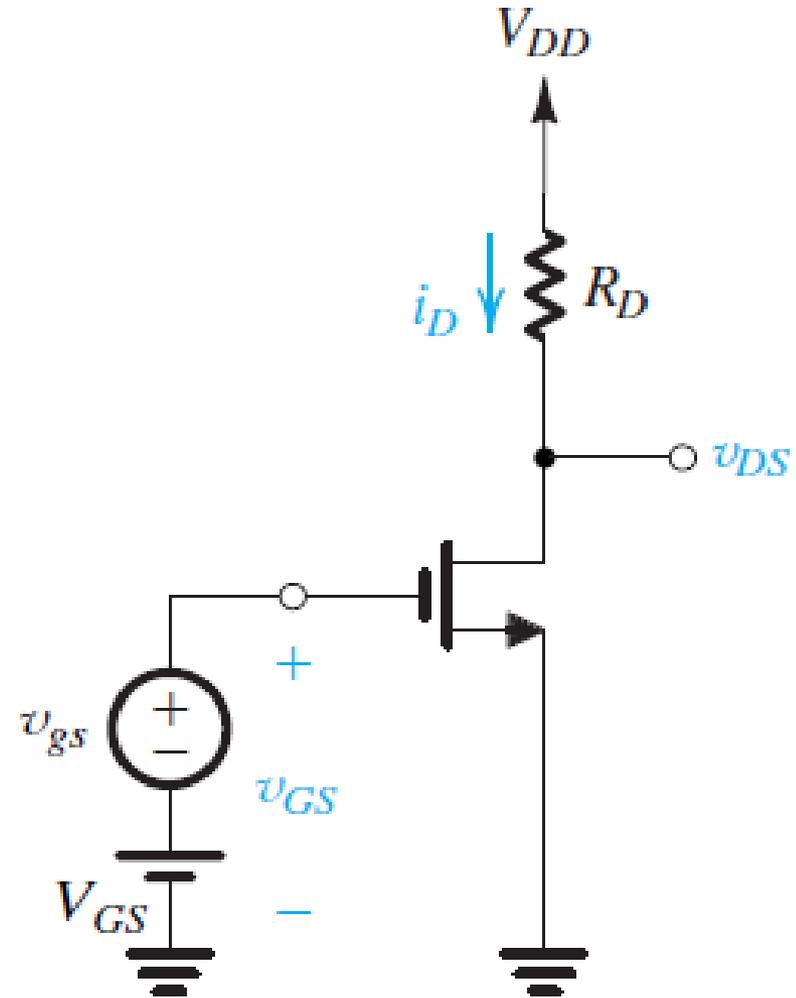
$$R_D = 17.5 \text{ k}\Omega$$

$$V_{GS} = 0.6 \text{ V}$$

a. Tentukan V_{OV} , I_D , dan V_{DS} , jika

$$v_{gs} = 0 \text{ V}$$

b. Tentukan besar penguatan A_v dengan analisis sinyal kecil



Step 1

Hitung nilai V_{OV} , I_D , V_{DS} , g_m
dan r_o

$$g_m = k_n V_{OV}$$

$$g_m = 4 \times 0.2 = 0.8 \text{ mA/V}$$

$$V_{OV} = 0.6 - 0.4$$

$$V_{OV} = 0.2 \text{ volt}$$

$$I_D = \frac{1}{2} k_n V_{OV}^2$$

$$I_D = \frac{1}{2} \times 4 \times (0.2)^2$$

$$I_D = 0.08 \text{ mA}$$

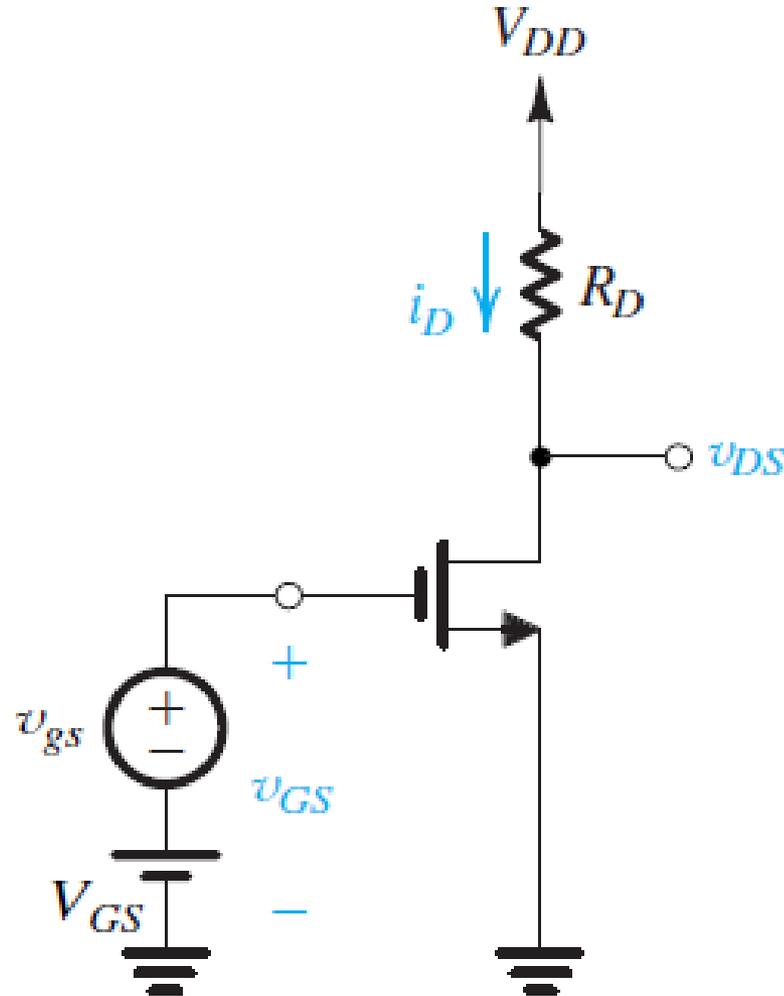
$$V_{DS} = V_{DD} - I_D R_D$$

$$V_{DS} = 1.8 - (0.08 \times 17.5)$$

$$V_{DS} = 0.4 \text{ volt}$$

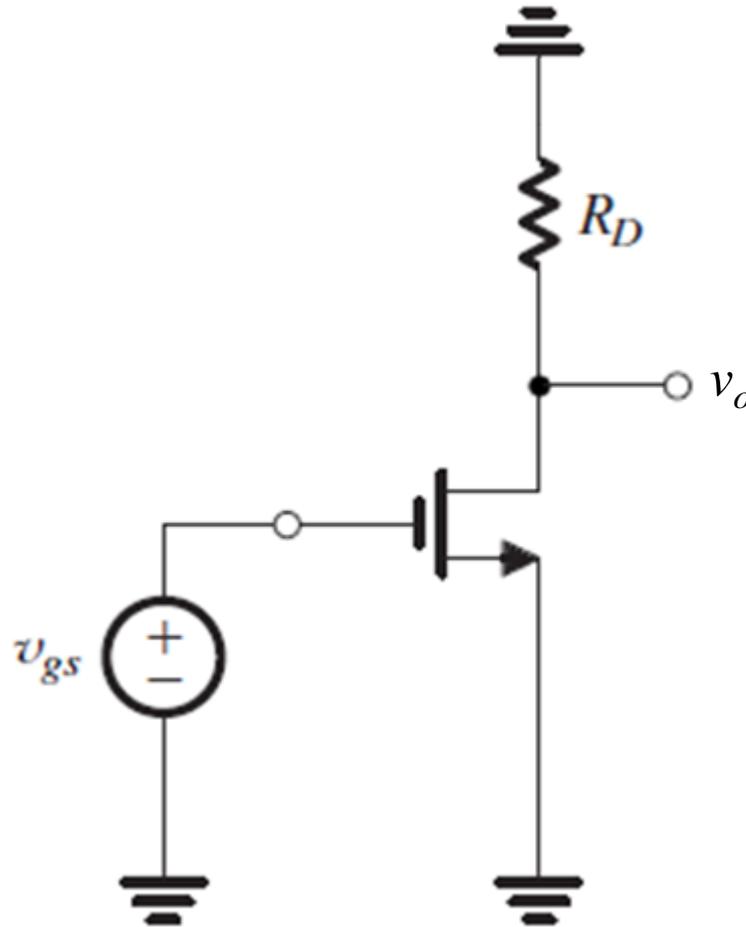
Step 2

Hilangkan sumber DC
 (jadikan short circuit)



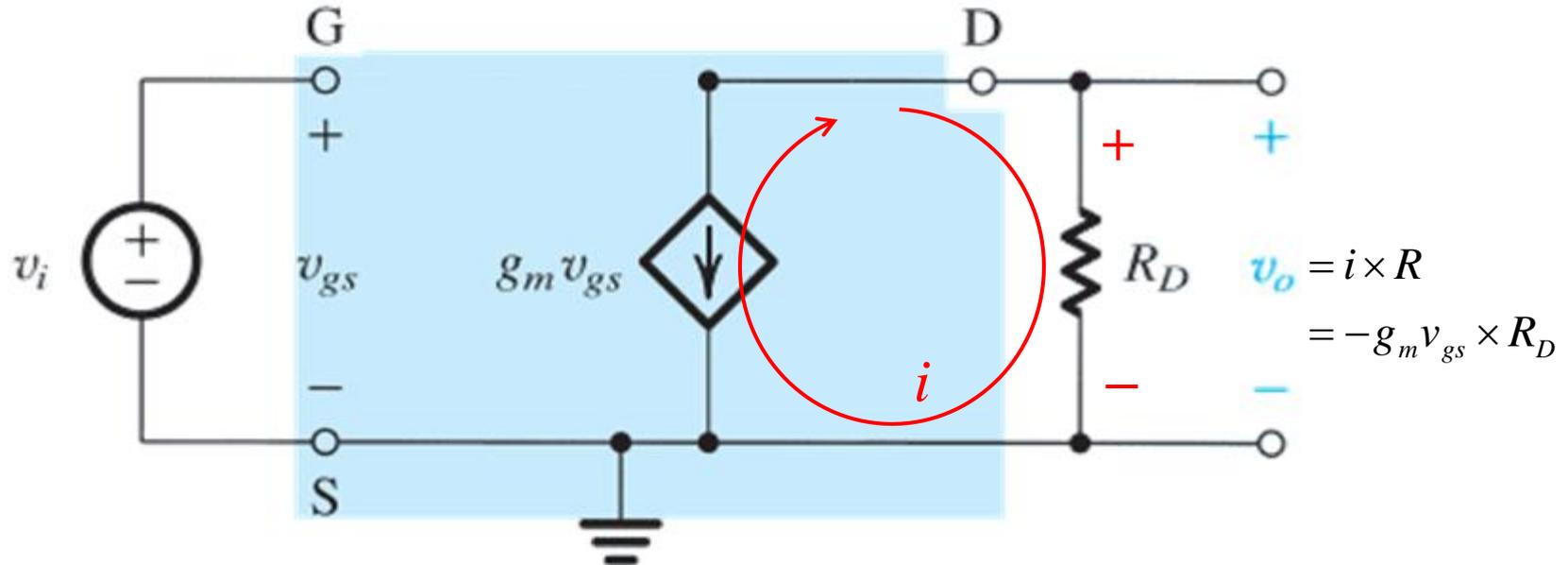
Step 2

Hilangkan sumber DC
(jadikan short circuit)



Step 3

Ubah menjadi model sinyal kecil



Jika diketahui:

$$V_t = 0.4 \text{ V}$$

$$k_n = 4 \text{ mA/V}^2$$

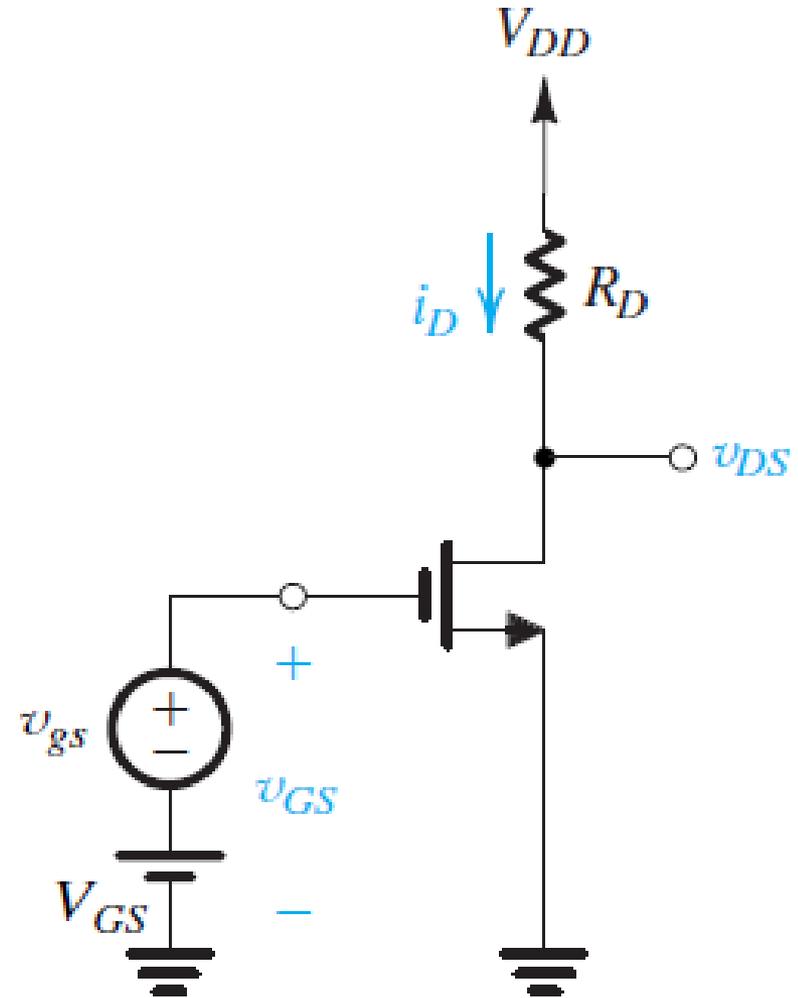
$$V_{DD} = 1.8 \text{ V}$$

$$R_D = 17.5 \text{ k}\Omega$$

$$V_{GS} = 0.6 \text{ V}$$

$$V_A = 50 \text{ V}$$

Tentukan besar penguatan A_v dengan analisis sinyal kecil



Step 1

Hitung nilai V_{OV} , I_D , V_{DS} , g_m
dan r_o

$$g_m = k_n V_{OV}$$

$$g_m = 4 \times 0.2 = 0.8 \text{ mA/V}$$

$$r_o = \frac{V_A}{I_D}$$

$$r_o = \frac{50}{0.08} = 625 \Omega$$

$$V_{OV} = 0.6 - 0.4$$

$$V_{OV} = 0.2 \text{ volt}$$

$$I_D = \frac{1}{2} k_n V_{OV}^2$$

$$I_D = \frac{1}{2} \times 4 \times (0.2)^2$$

$$I_D = 0.08 \text{ mA}$$

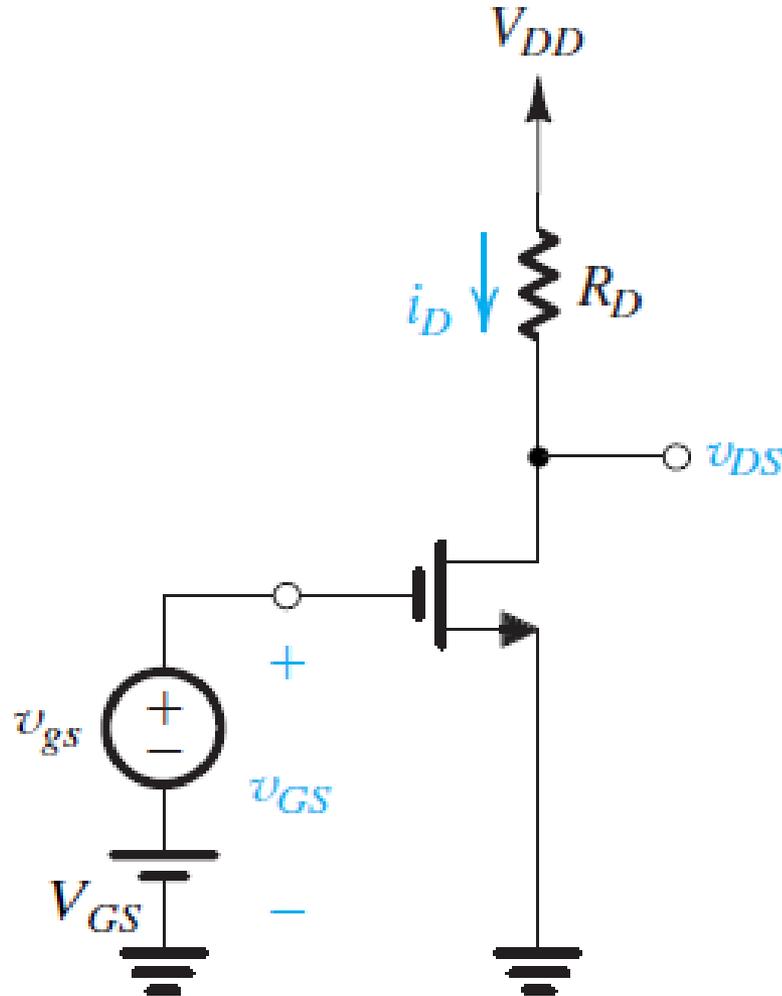
$$V_{DS} = V_{DD} - I_D R_D$$

$$V_{DS} = 1.8 - (0.08 \times 17.5)$$

$$V_{DS} = 0.4 \text{ volt}$$

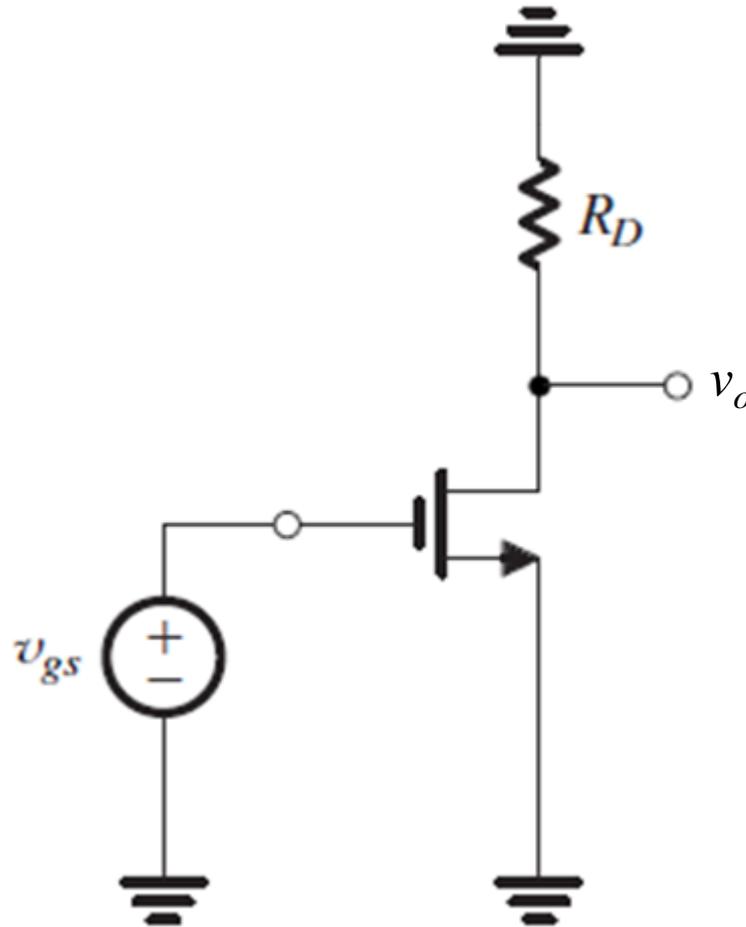
Step 2

Hilangkan sumber DC
 (jadikan short circuit)



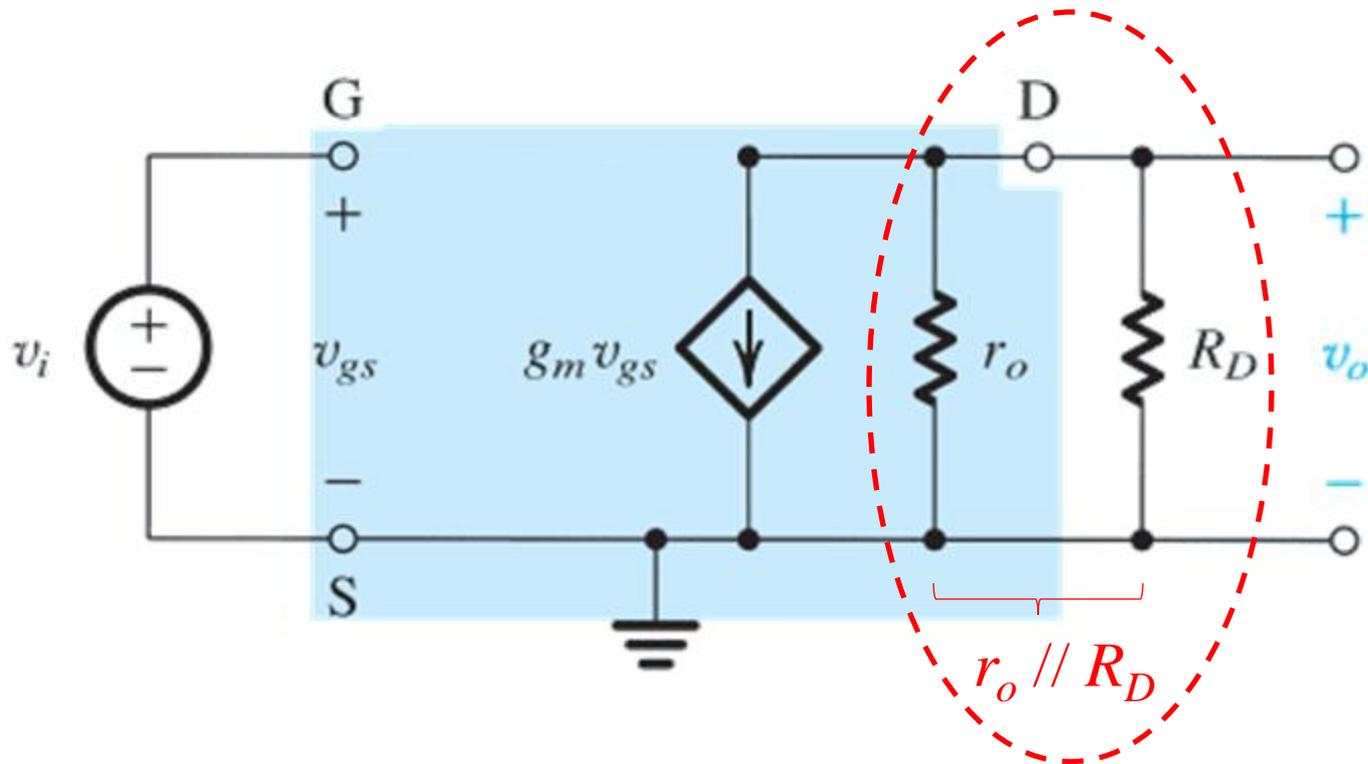
Step 2

Hilangkan sumber DC
(jadikan short circuit)



Step 3

Ubah menjadi model sinyal kecil



Step 3

Ubah menjadi model sinyal kecil

